

# 太陽光電鈍化技術

## Passivation Technology for Photovoltaics

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# Outline

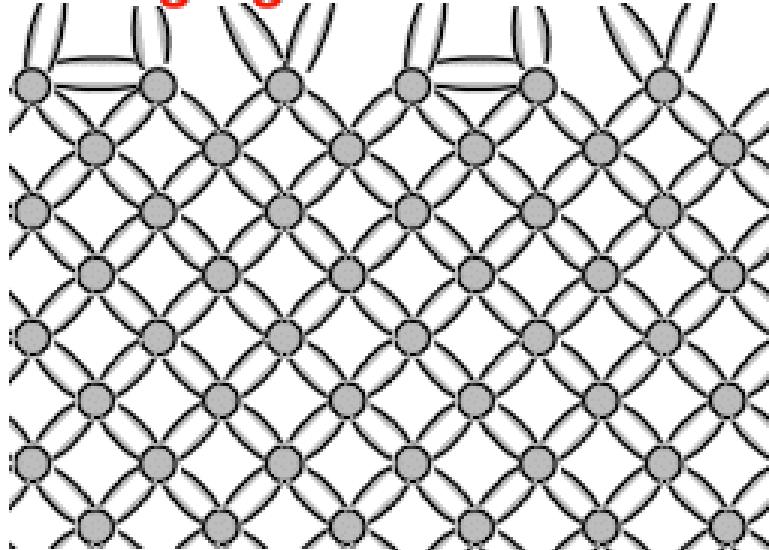
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- **Introduction**
- **Passivation Technologies**
- **GO for Solar Cell Passivation**
- **GO for Solar Water Splitting**
- **Summary**

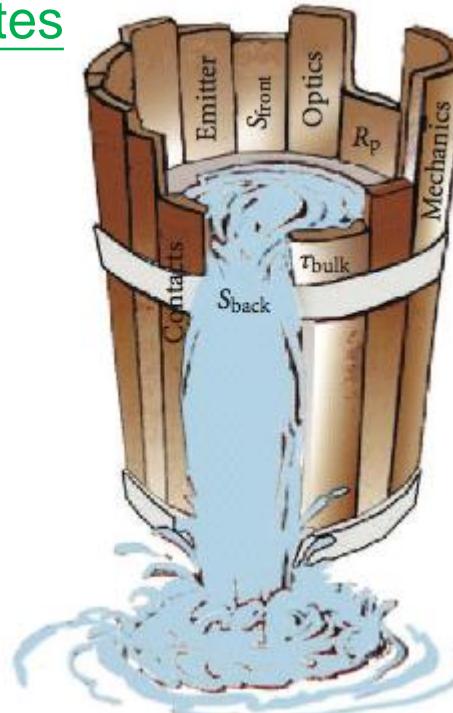
# Why Passivation(鈍化)?

Recombination Occurs at surface

**Dangling bonds at surface**



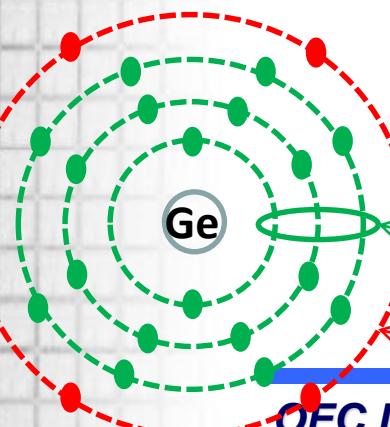
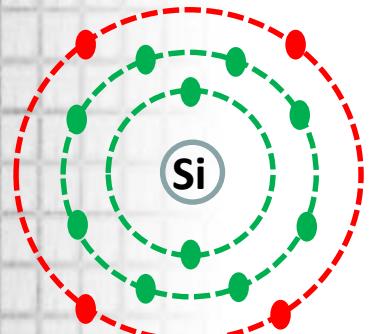
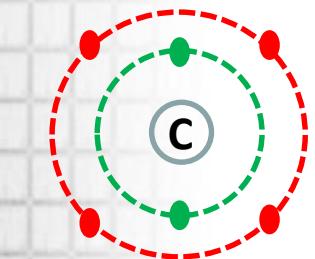
Rear Surface Recombination Dominates



- 太陽電池(矽)的表面  
=> 矽晶格的邊界(晶格嚴重的終結)  
=> 成為高復合的所在處
- 傳統(AI BSF)太陽電池遭受矽與其下金屬介面高表面複合速率( $S_{back}$ )所害

Ref.: <http://www.pveducation.org/>  
S. W. Glunz, *Advances in OptoElectronics*

# 半導體常見元素



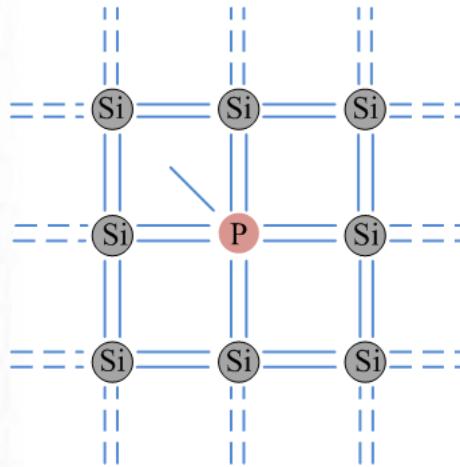
		三族 (有三個 價電子)	四族 (有四個 價電子)	五族 (有五個 價電子)	
Group	Period	II	III	IV	VI
2			B Boron	C Carbon	N Nitrogen
3			Al Aluminum	Si Silicon	P Phosphorus
4		Zn Zinc	Ga Gallium	Ge Germanium	As Arsenic
5		Cd Cadmium	In Indium	Sn Tin	Sb Antimony
6		Hg Mercury			Te Tellurium

核心電子：穩定(之後不畫出)

價電子：化學反應/共價鍵都靠它們

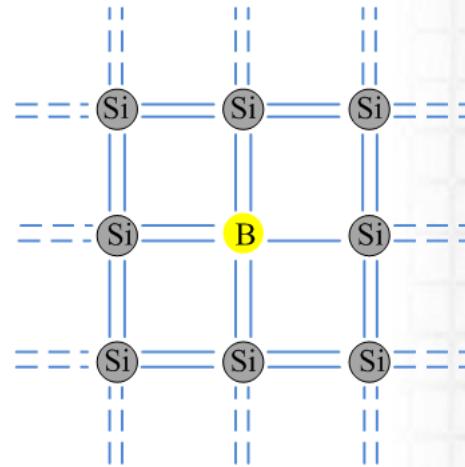
# 在四族半導體內摻三/五族元素

n型半導體(摻五族)



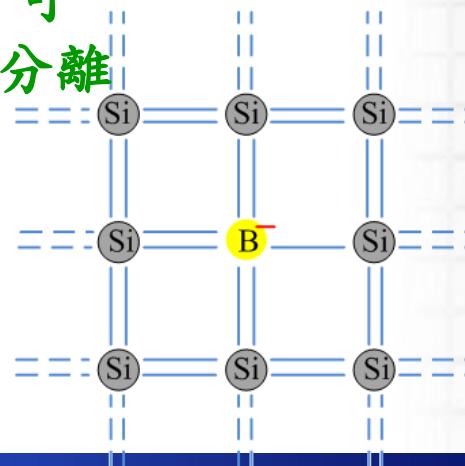
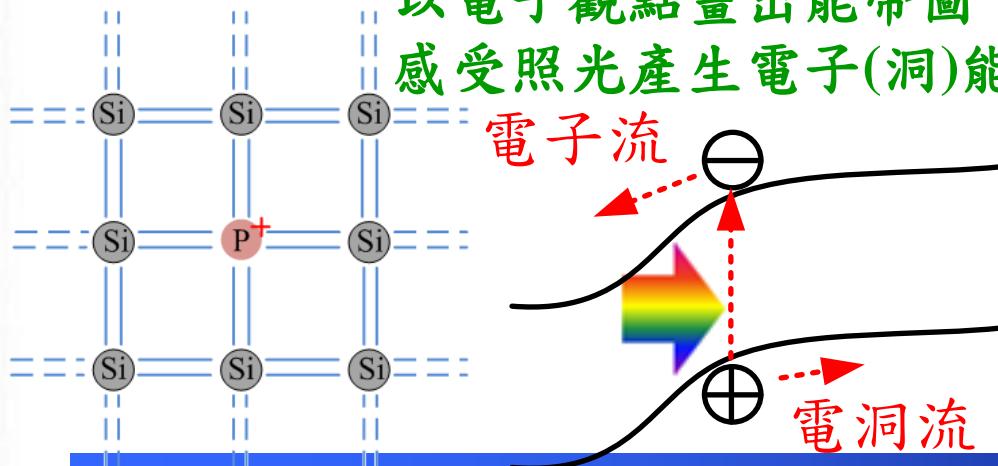
電子跑走，留下帶正電P離子

p型半導體(摻三族)

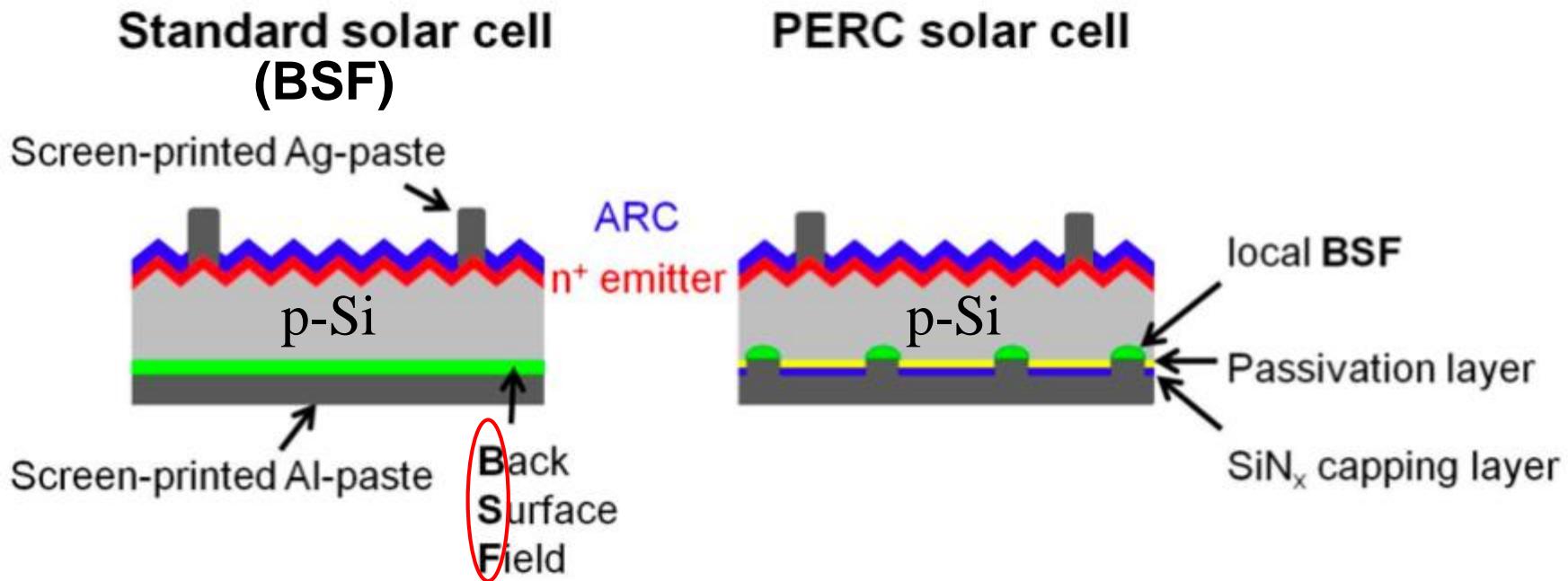


電洞跑走，留下帶負電B離子

以電子觀點畫出能帶圖，可  
感受照光產生電子(洞)能分離



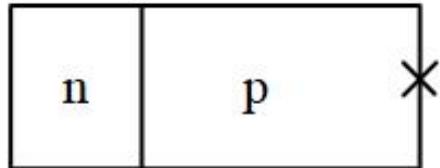
# pn太陽電池架構早期採BSF，目前多改PERC



Ref.:

<https://www.solarchoice.net.au/blog/news/perc-solar-cells-steadily-gaining-steam-in-pv-160215>

## 結構視角



## 能帶視角



## 爸爸視角

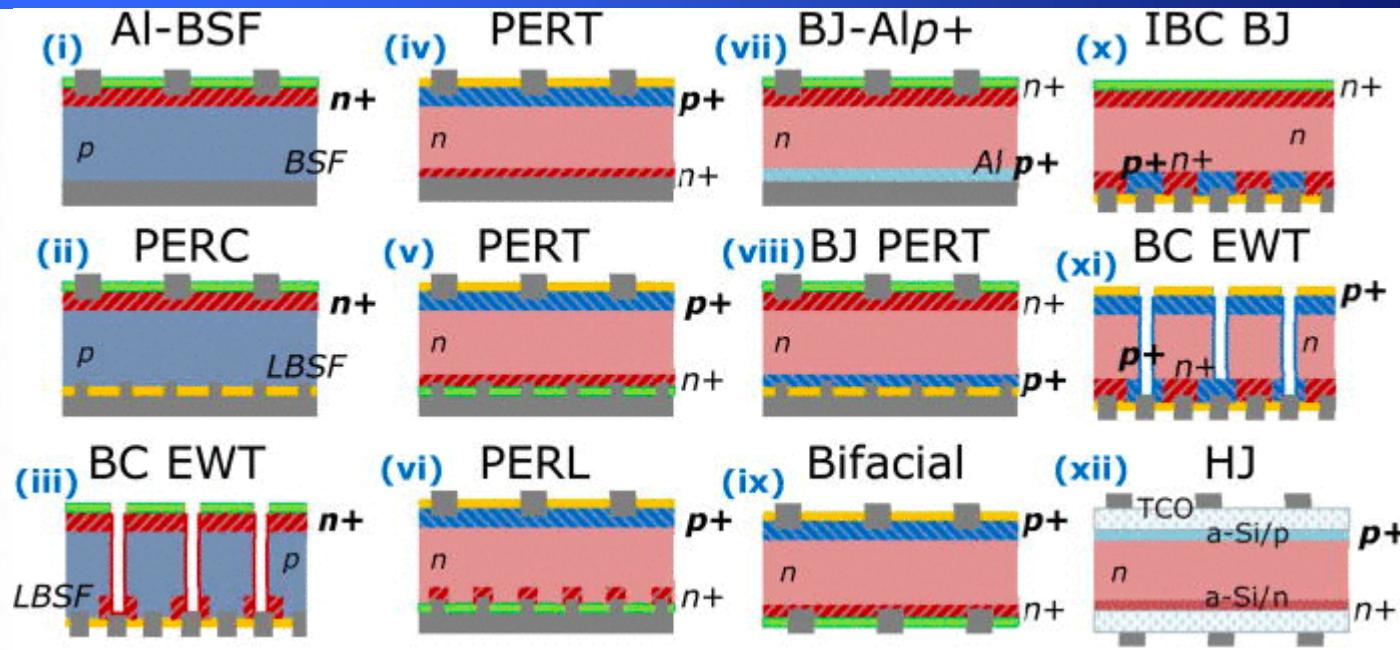


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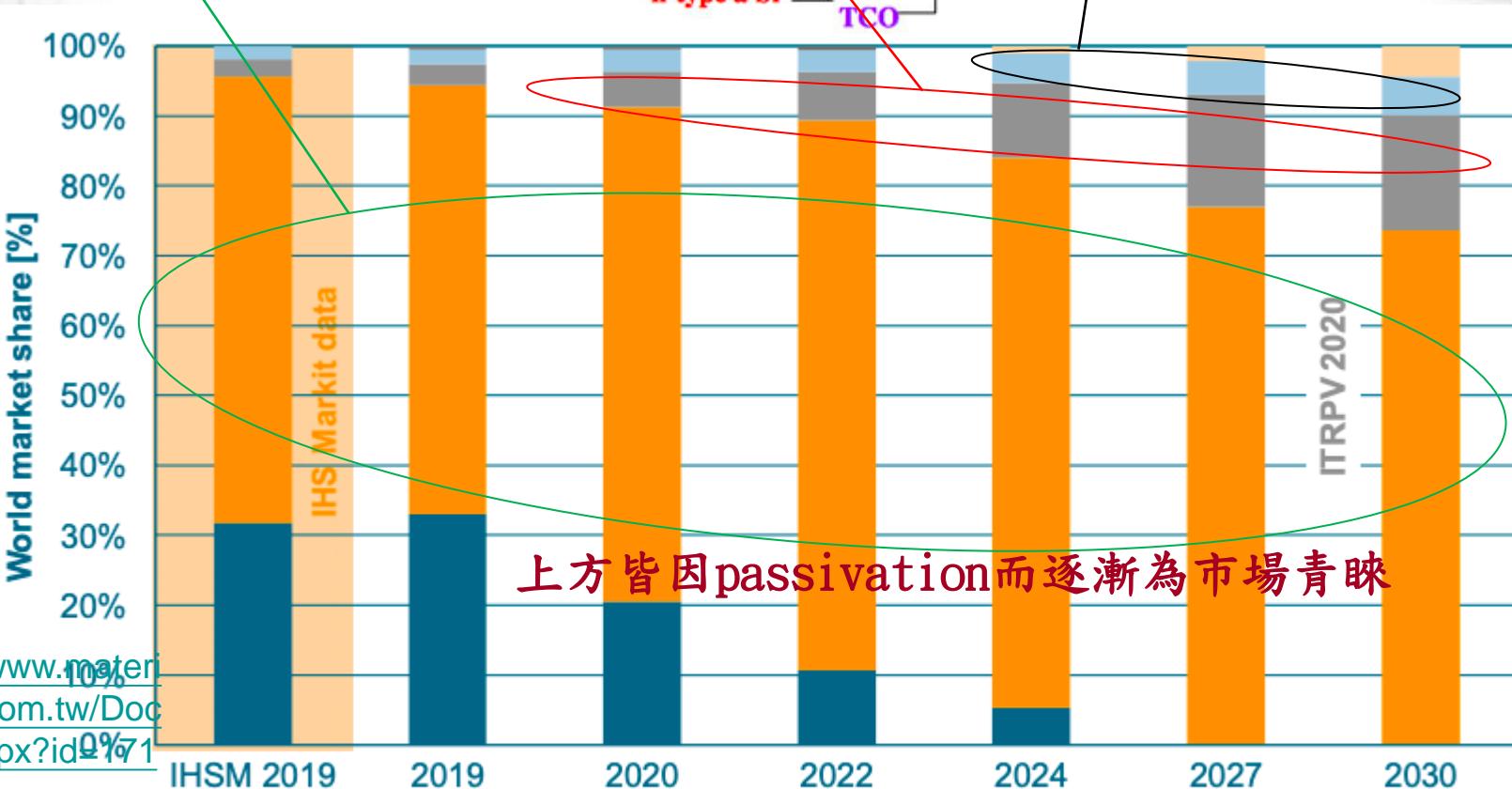
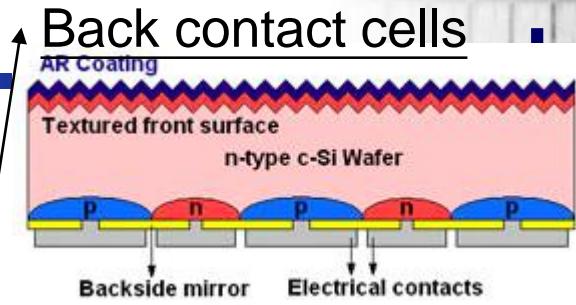
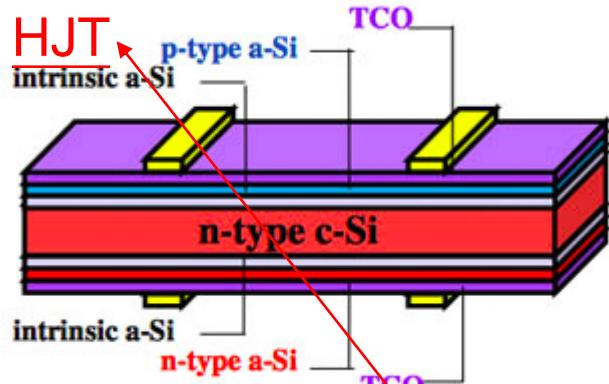
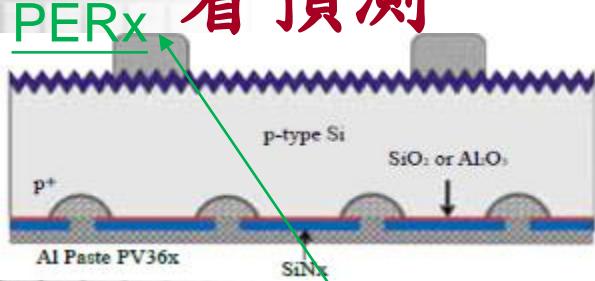
# Cell技術千百種，要關注哪一種？



Various solar cell concepts based on  $p$ - and  $n$ -type Si wafers. (i) Full Al-BSF; (ii) passivated emitter and rear (PERC) cell; (iii) backcontacted emitter wrap through (BC EWT) cell; (iv), (v) passivated emitter and rear totally diffused (PERT) cell; (vi) passivated emitter and rear locally diffused (PERL) cell; (vii) backjunction Al alloyed rear emitter ("BJ-Alp+") cell; (viii) backjunction PERT cell; (ix) bifacial cell; (x) interdigitated backcontacted backjunction (IBC BJ) cell; (xi) backcontacted emitter wrap through (BC EWT) cell; (xii) heterojunction (HJ) cell.

Ref:<http://doi.org/10.1116/1.4728205>

# 看預測



Ref.:

<https://www.materialsnet.com.tw/DocPrint.aspx?id=0%71>

07

<http://www.udel.edu/iec/iecResearchSilicon.html>

■ BSF cells

■ HJT

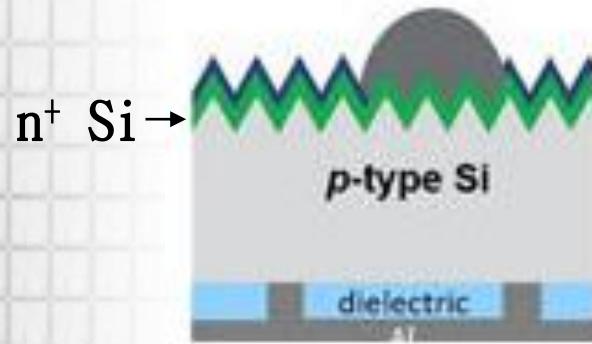
■ Si-based tandem cells

■ PERC/PERL/PERT/TOPCON cells

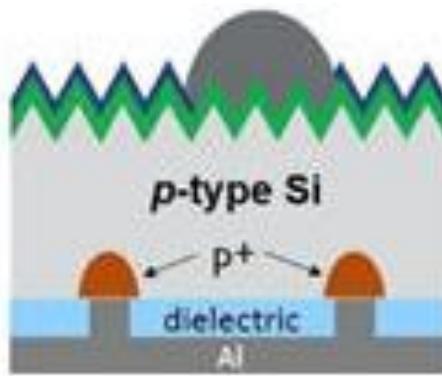
■ back contact cells

■ Metal Wrap Through cells

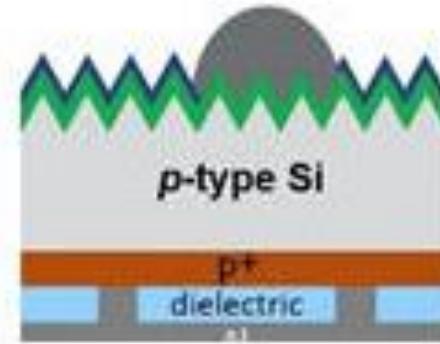
# PERx Series



PERC  
(Passivated  
Emitter and  
Rear Contact)



PERL  
(Passivated  
Emitter and Rear  
Locally diffused)



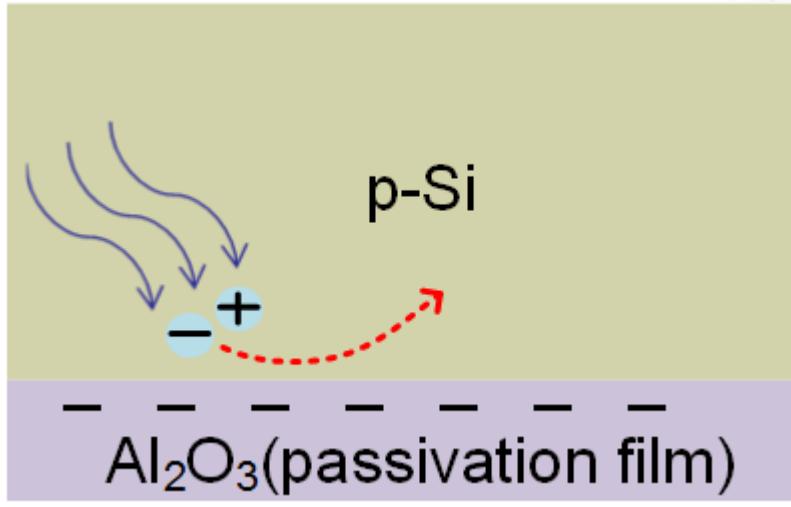
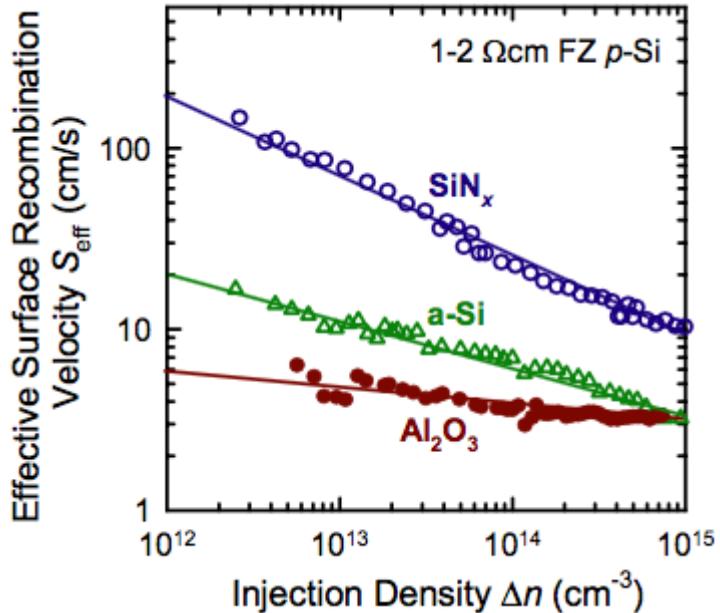
PERT  
(Passivated  
Emitter and  
Rear Totally  
diffused))

效率能比BSF太陽電池高的關鍵

- 正面利用SiN<sub>x</sub>作為n-Si的passivation(有些BSF也如此)
- 背面利用Al<sub>2</sub>O<sub>3</sub>等dielectric作為p-Si的passivation

Ref.: [www.photonicsonline.com/doc/how-to-push-conventional-sided-contacted-solar-cells-to-the-max-0001](http://www.photonicsonline.com/doc/how-to-push-conventional-sided-contacted-solar-cells-to-the-max-0001)

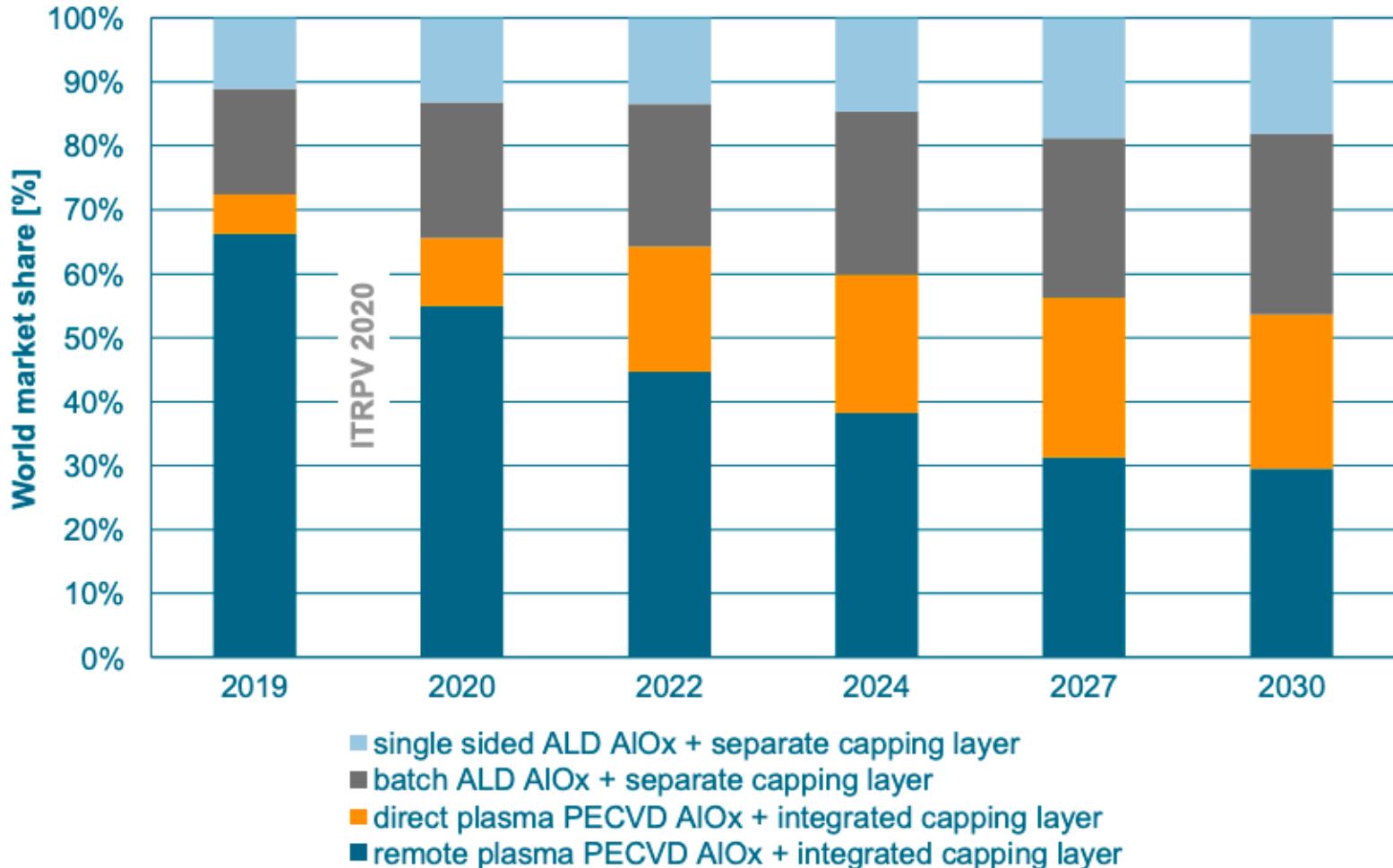
# Passivation (dielectric) Materials



- a-Si or  $\text{SiO}_2$ : 減少表面斷鍵(dangling bonds)，減少複合site
- $\text{SiN}_x(+)$  or  $\text{Al}_2\text{O}_3(-)$  or GO(-): 藉由薄膜層內的固定電荷來提供場效鈍化(field effect passivation)

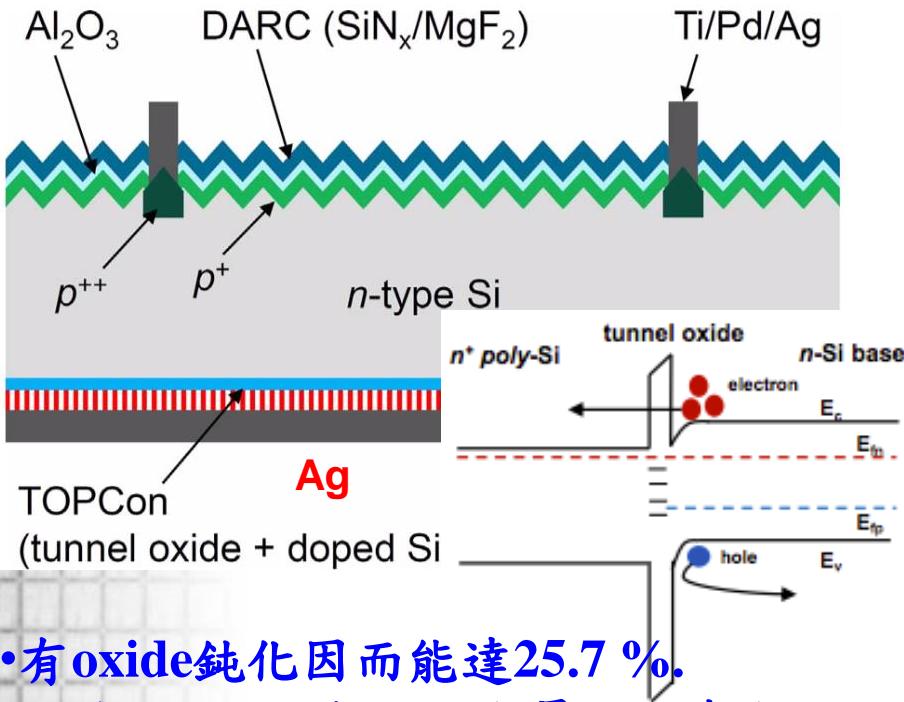
Ref.: Jan Schmidt, EU PVSEC 2008

## Different rear side passivation technologies

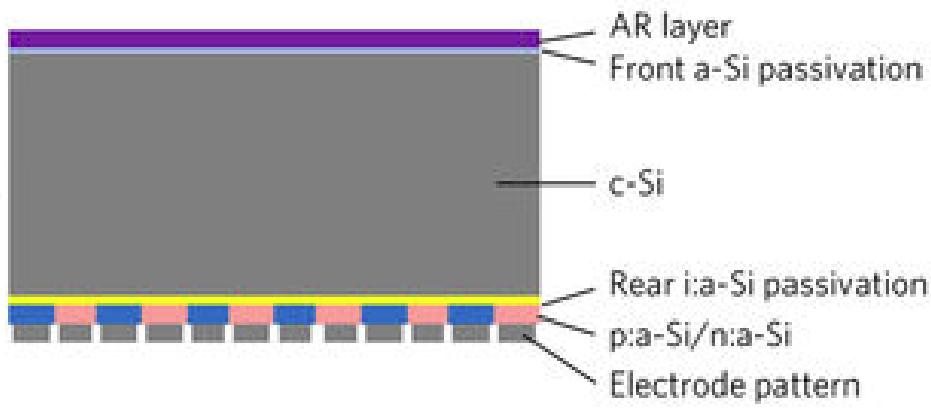


# New Passivation Technology

## Tunnel Oxide Passivated Contact (TOPCon)



## Heterojunctions (HJ)+ interdigitated back contact (IBC)



- 有 oxide 鈍化因而能達 25.7 %。
- 不像 PERx 仍有部分金屬接觸處無法鈍化， $n^+$ Si/n-Si 所成的 carrier-selective passivating contact 整個面都允許多數載子(e) 通過而阻止少數載子(h) 往該方向傳輸。

- 結合下兩結構優點達 26.7 % 目前紀錄
- HJ: a-Si layer passivates the c-Si surface
- IBC: 表面無電極阻擋入射光

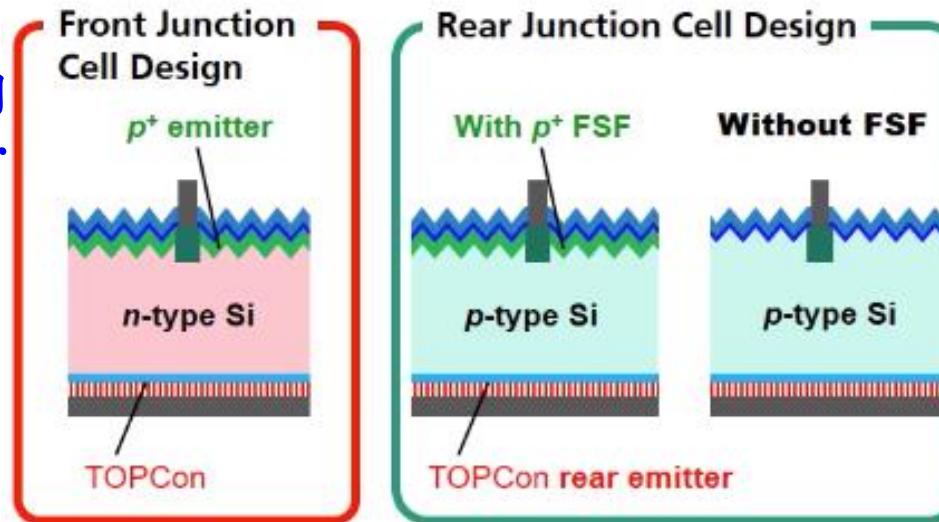
Ref.: S. W. Glunz, SEMSC, 2017  
K. Yashikawa et al., Nature energy 2017.

# TOPCon再進化

n-Si基座缺點：

- 照光所產生的電洞需要藉由 $p^+$  emitter傳導，摻雜太低導電差；摻雜太高則高複合

Ref.: A. Richter  
(Fraunhofer Institute for  
Solar Energy Systems  
(ISE), Silicon PV 2020)



改成p-Si基座：

- 背部就由TOPCon協助電子傳導(似pn接面)，已有整面Ag無須橫向傳導(不怕電子傳輸差)
- 正面整塊都是p型，電洞傳輸也不太需要靠高摻雜的FSF (front surface field)

Design	$V_{oc}$ (mV)	FF (%)	$J_{sc}$ (mA/cm <sup>2</sup> )	$\eta$ (%)
Front junction [1,2]	724	83.1	42.9	25.8
Rear junction without FSF [3]	732	84.3	42.1	26.0

• TOPCon潛力：

BSF、PERx升級成TOPCon改裝少、成本少，比起HJT從頭來過好

• TOPCon挑戰：

要解決鍍poly-Si時繞鍍到正面，多流程造成之成本與穩定度問題

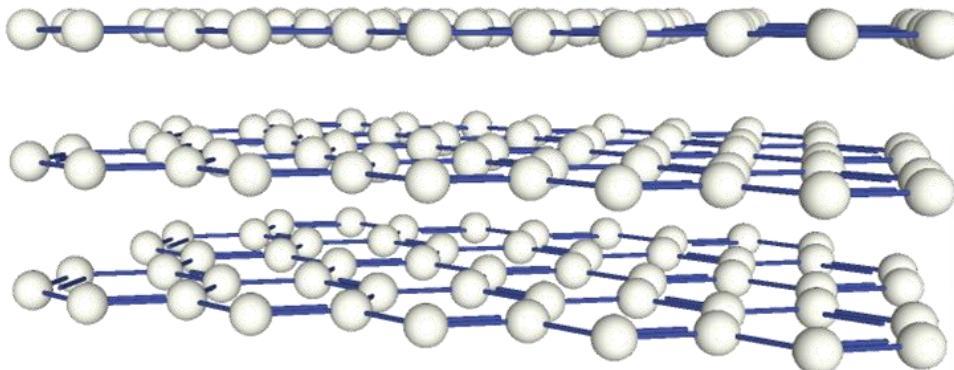
# Outline

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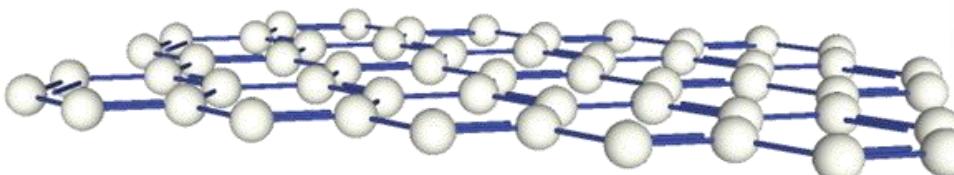
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# *Graphene vs. Graphene Oxide*

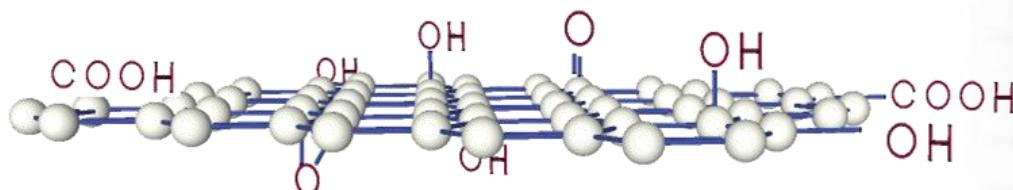
- Graphite



- Graphene

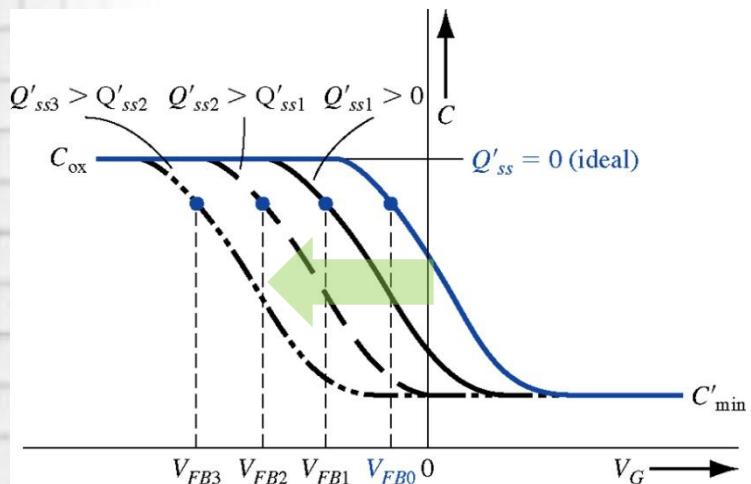


- Graphene Oxide(GO , 氧化石墨烯)



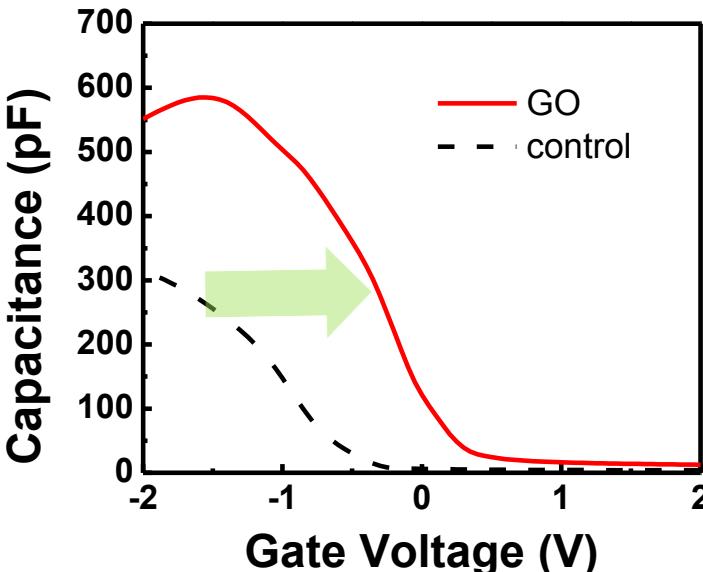
# Our Finding: Negative Charge in GO

- From textbook,  
we know :  
w/ positive charge



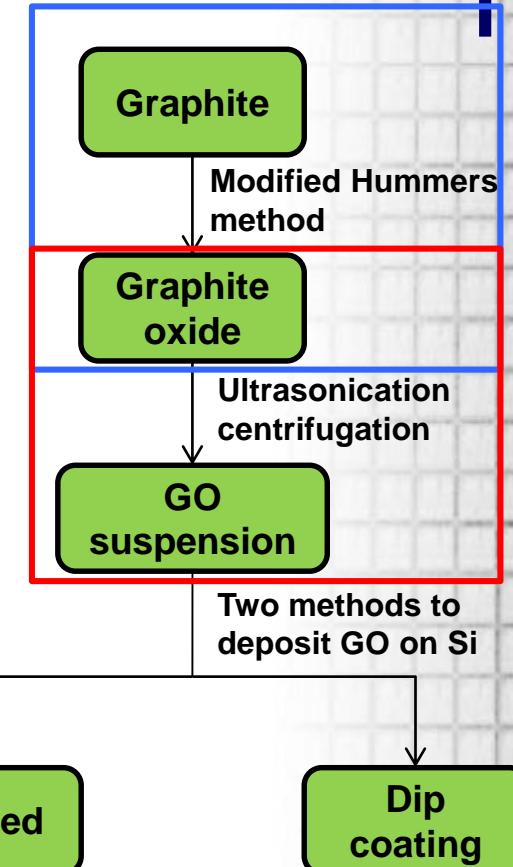
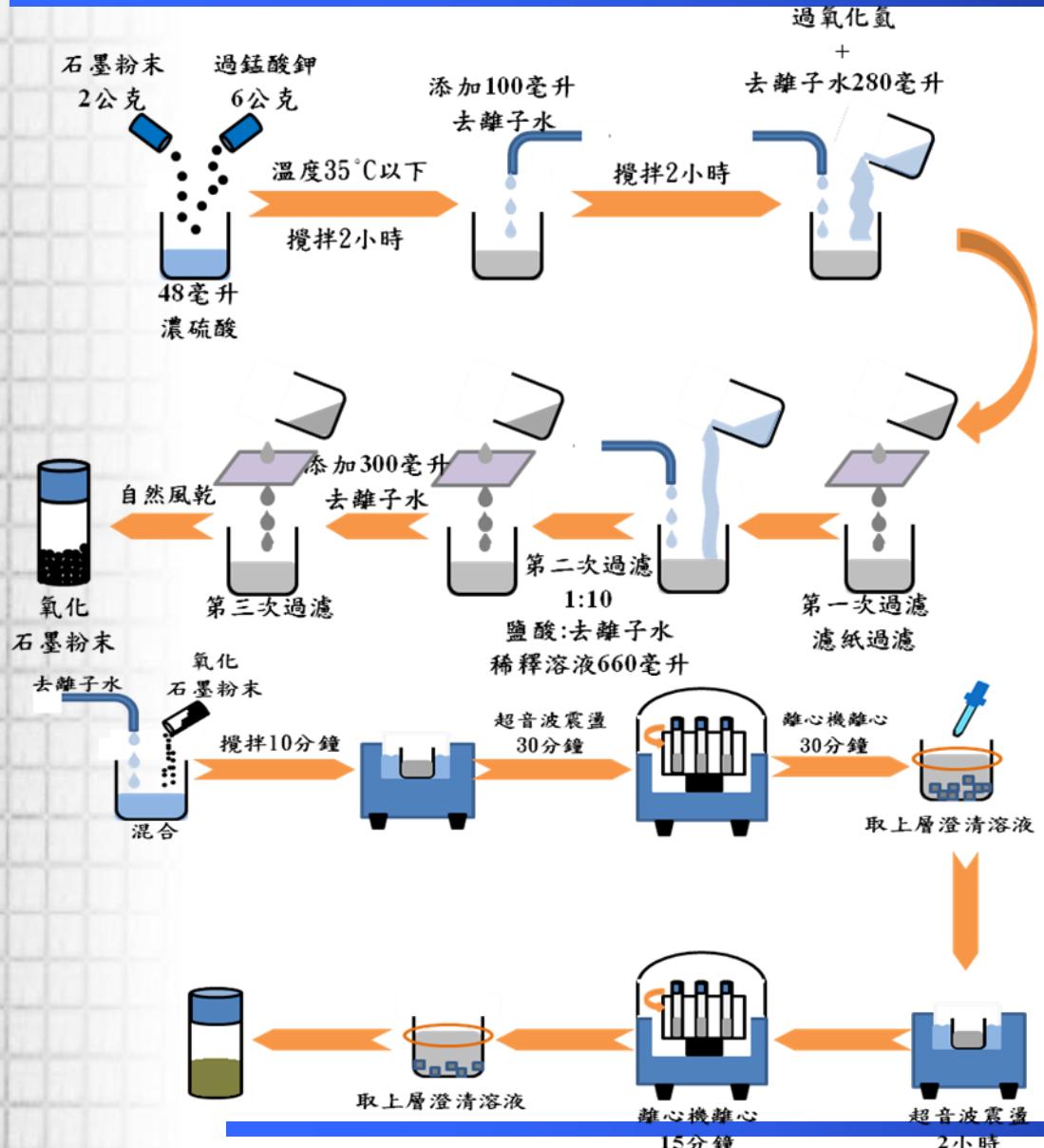
$$V_{FB} = \phi_{ms} - \frac{Q'_{ss}}{C_{ox}}$$

- w/ negative charge



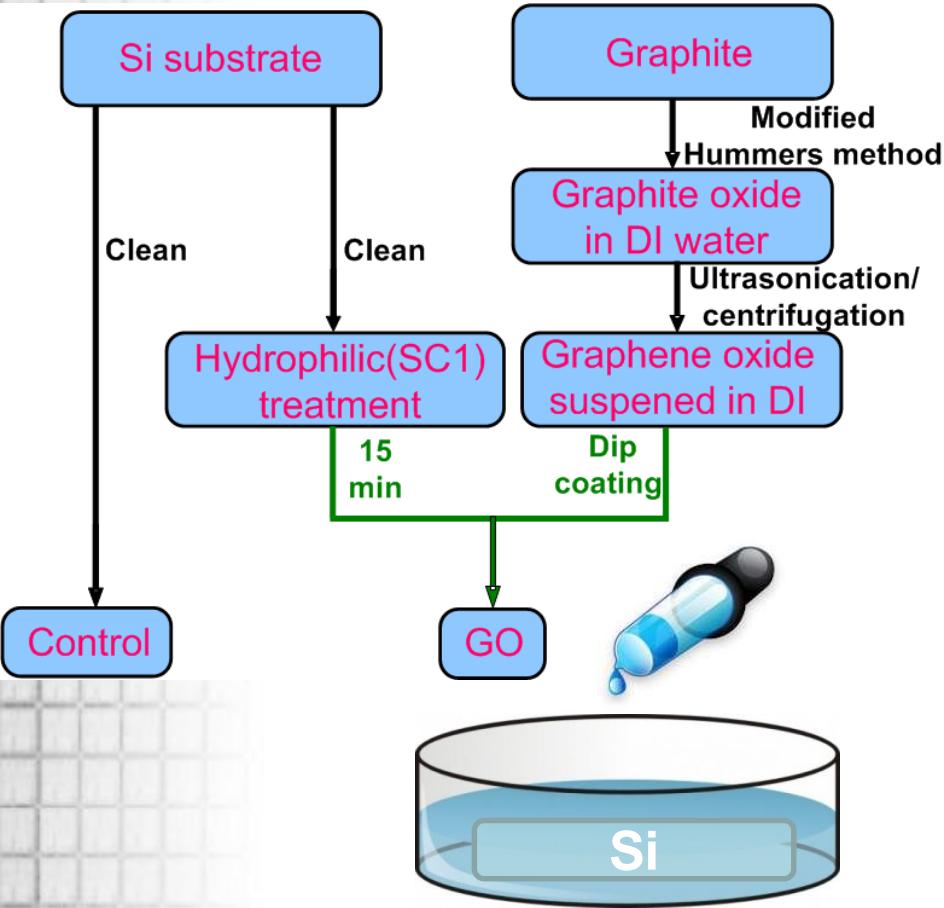
- Charge density:  $-6 \times 10^{12} / \text{cm}^2$
- Other common used materials:
  - $\text{Al}_2\text{O}_3: -3 \times 10^{12} / \text{cm}^2$
  - $\text{SiN}_x: 10^{12} / \text{cm}^2$

# Our procedure to prepare GO film

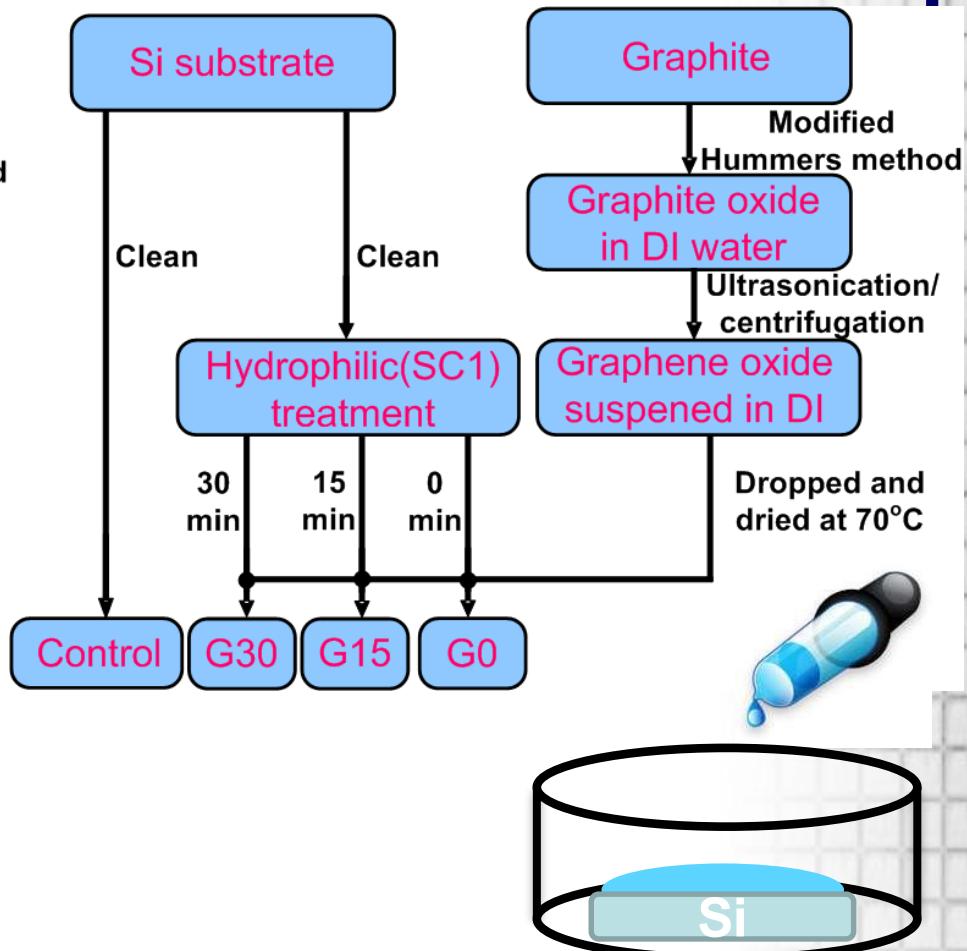


# Ways to deposit GO film

## Dip coating :

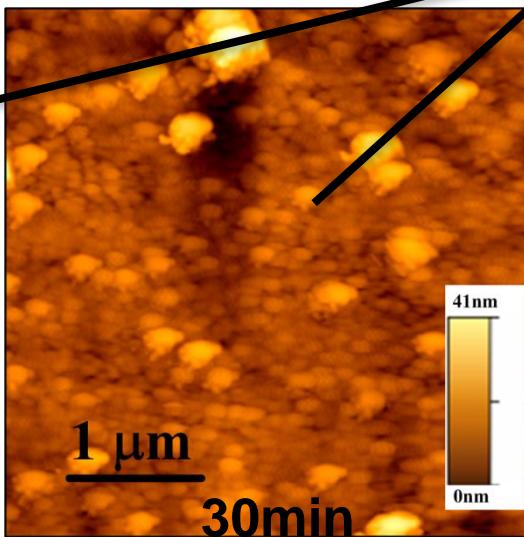
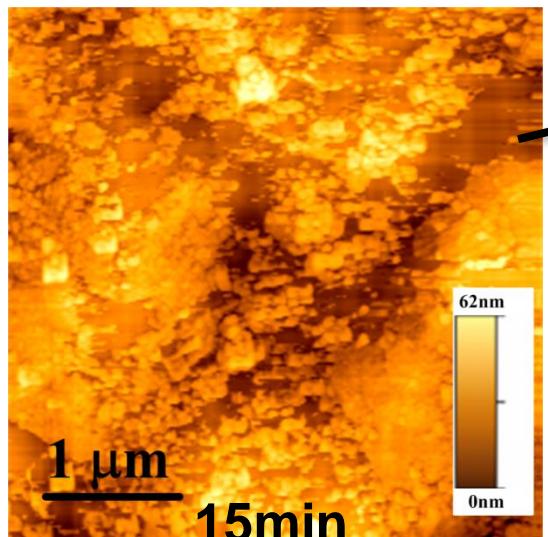
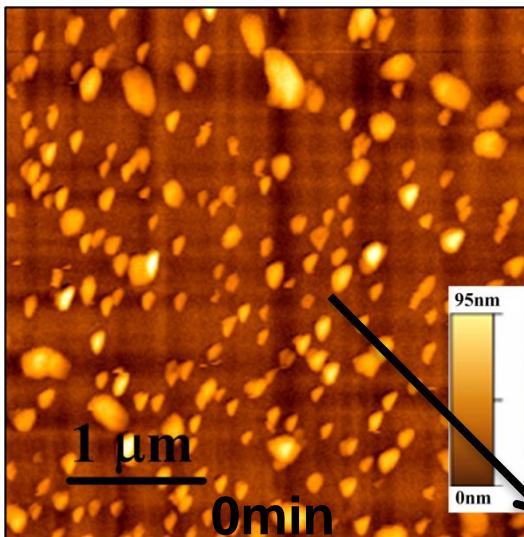
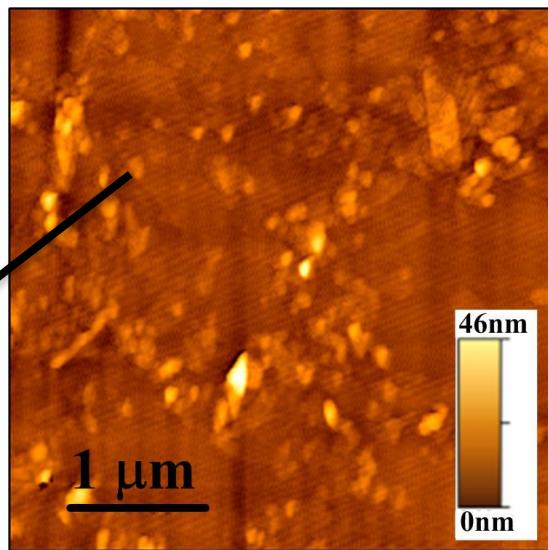


## Dropped :

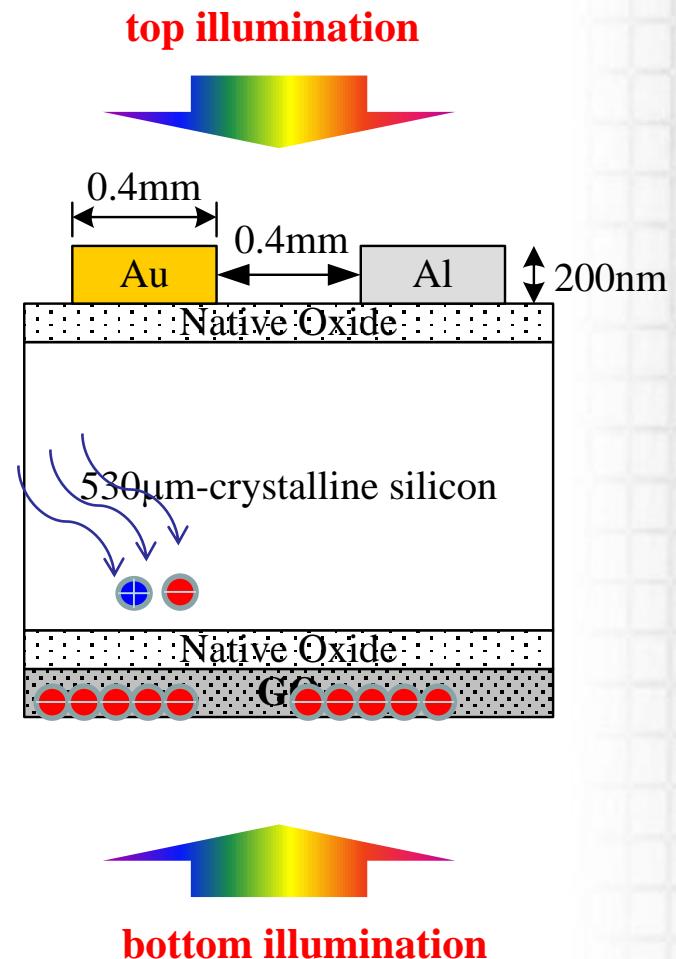
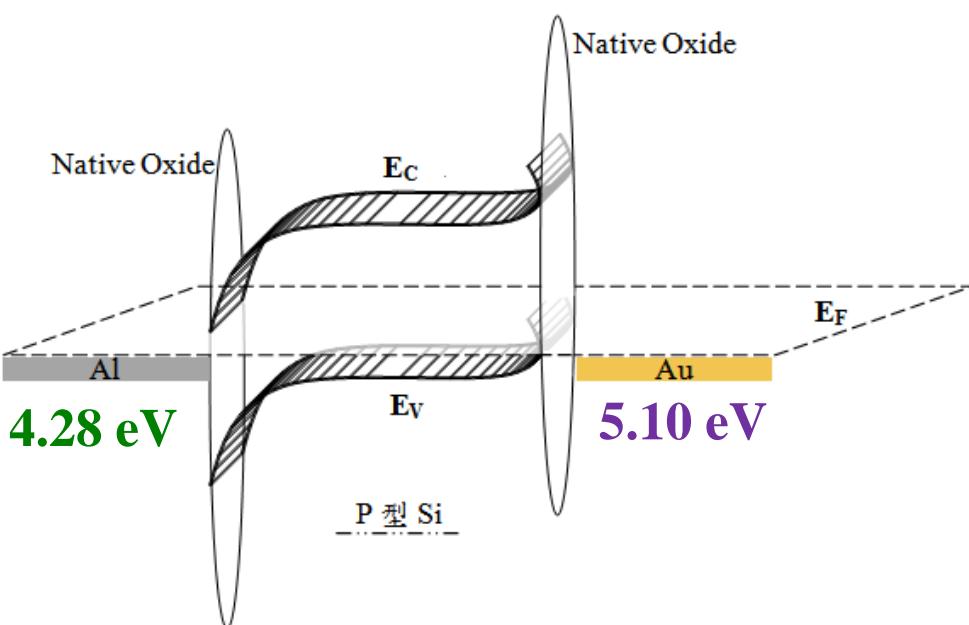


# 表面形貌 by Atomic Force Microscope(AFM)

Dip coating

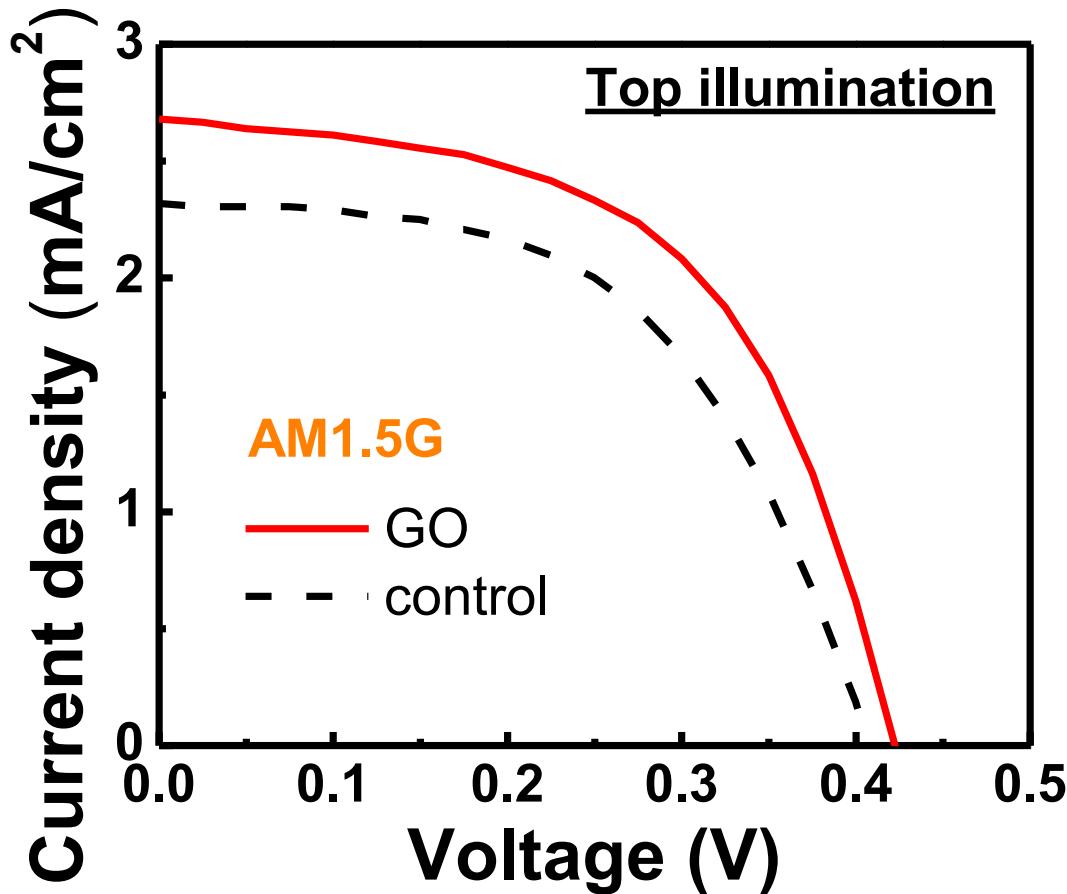


# Two-metal Cell Passivation by GO

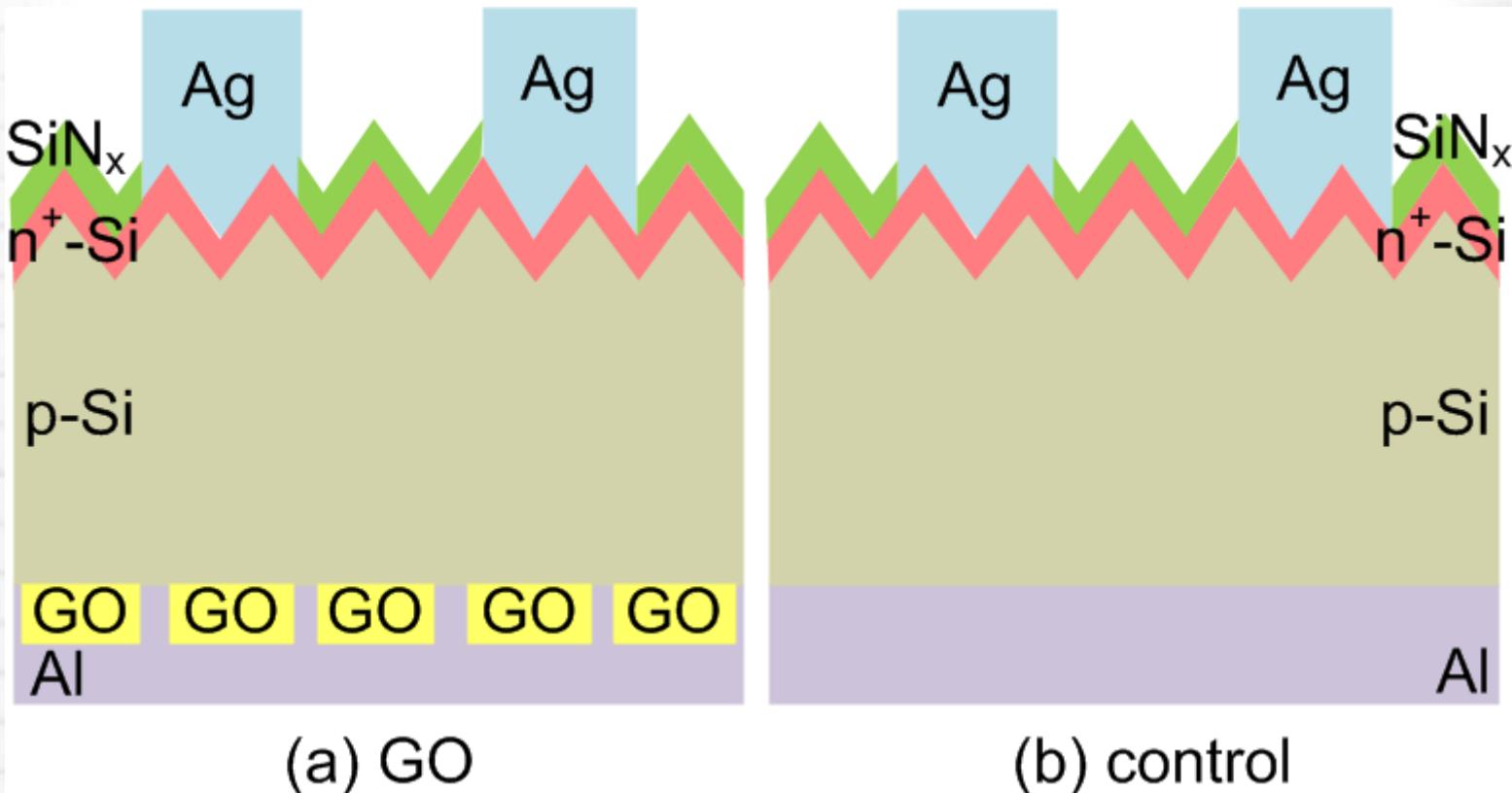


# GO 確實能提升Two-Metal Cell之表現

- GO introduction contributes to 21 % enhancement on the efficiency.
- But only from 0.52 to 0.63 %



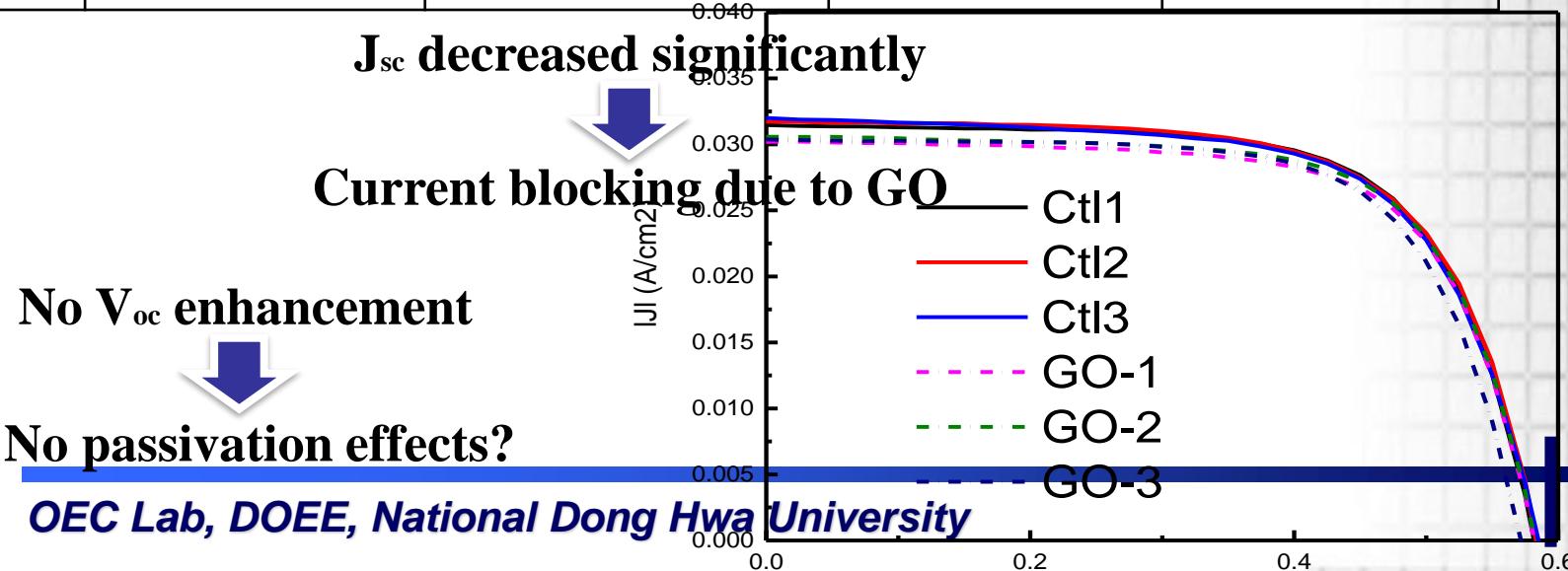
# Demonstration on Si pn-junction Cells



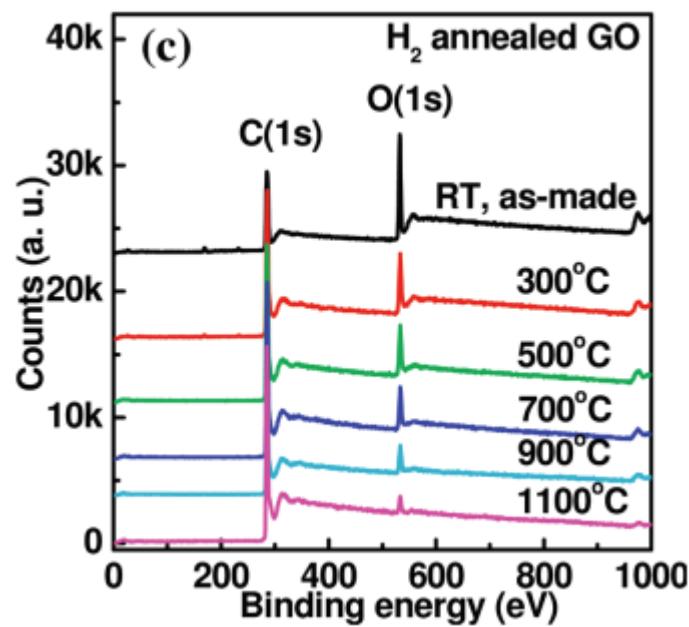
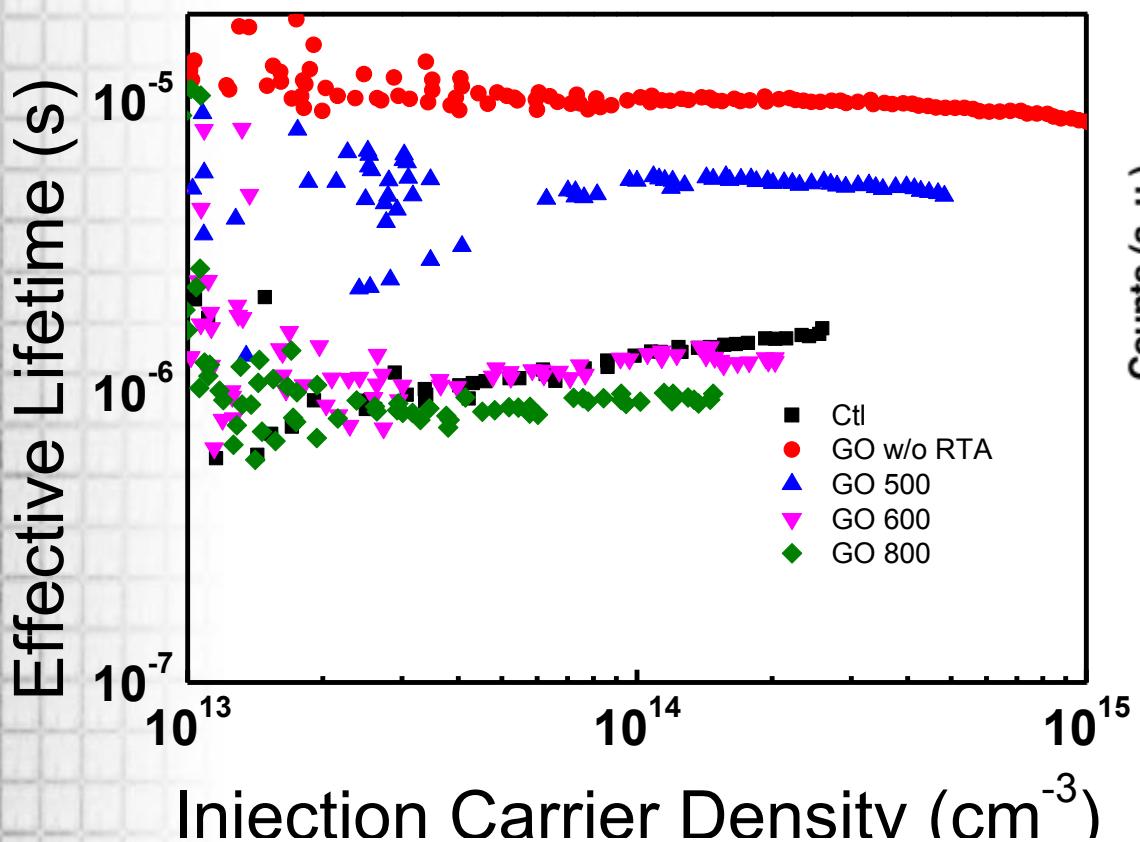
- 為了說明我們的GO有用於業界鈍化的價值  
=>得在商用pn太陽電池上展現GO也能提升效率  
=>下一頁我們比較在p-Si背面是否有蓋GO鈍化層的電池表現

# I-V Characteristic Improvement

	$V_{oc}$ (V)	$J_{sc}$ (mA/cm <sup>2</sup> )	FF	$\eta$ (%)
Ctl1	0.582	31.46	0.75	12.45
Ctl2	0.583	31.72	0.74	12.38
Ctl3	0.585	32	0.73	12.33
GO-1	0.582	30.19	0.76	12.02
GO-2	0.583	30.58	0.76	12.23
GO-3	0.572	30.37	0.75	11.89



# 高溫製程會消磨掉GO所提升的載子壽命



- Ref. J. AM. CHEM. SOC. 2009, 131, 15939
- O peak decreases as T increasing
- Passivation due to GO (fixed charge) may degrade.

• 網印的燒結參數：

4 s to 400°C (keep 1 min)

7 s to peak T (800 for ex) (keep 4s)

• 上圖說明了商用太陽電池中網印的高溫製程，衰退了太陽電池中的載子壽命 (lifetime)

# UNSW最近也發表了GO鈍化研究，但仍未用於電池

Lifetime接近1ms  $\tau_{\text{eff}}$  ( $\mu\text{s}$ )

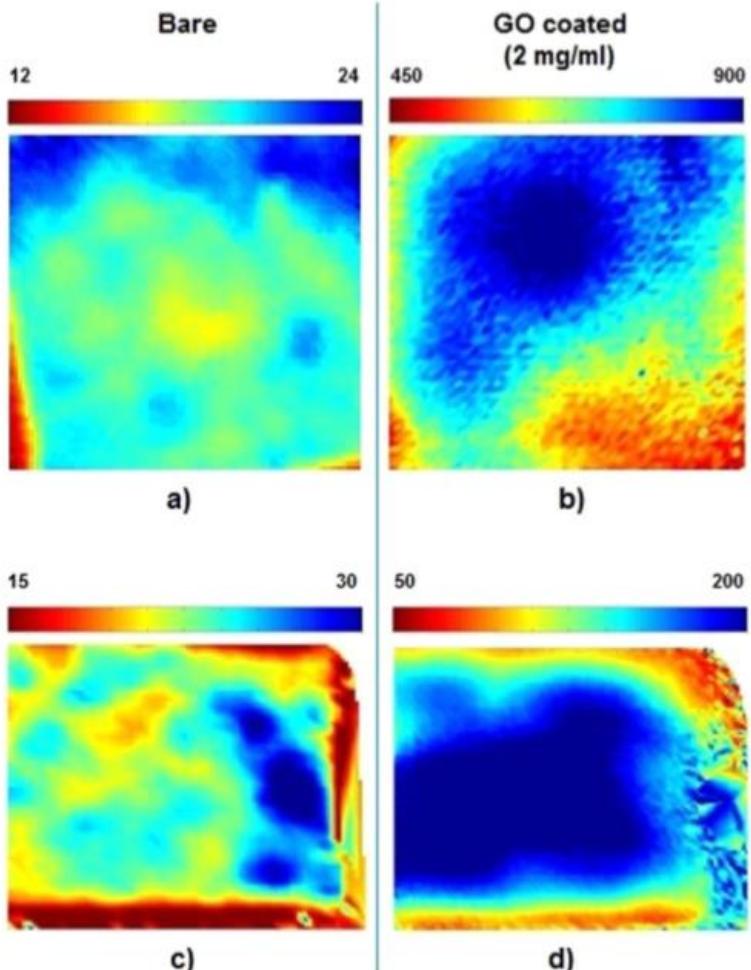


Fig. 1. Effective lifetime maps of a DSP FZ p-type ( $> 1000 \Omega\cdot\text{cm}$ ) silicon sample (a) bare and (b) GO coated, and a SSP Cz p-type ( $2.8 \Omega\cdot\text{cm}$ ) silicon sample (c) bare and GO coated.

XPS確認GO確有負電荷引起表面空乏

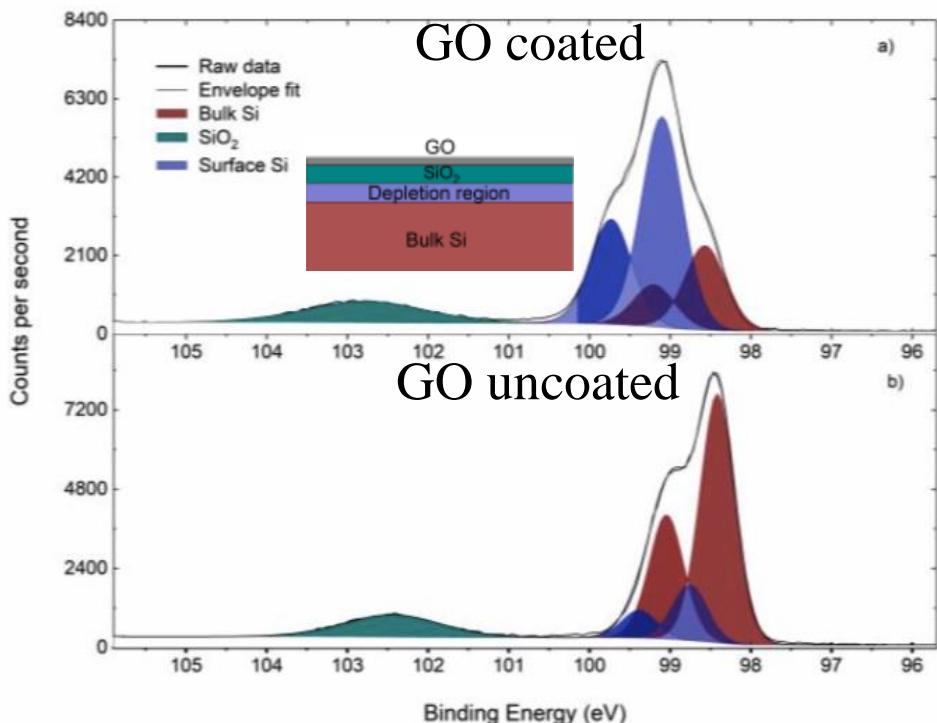
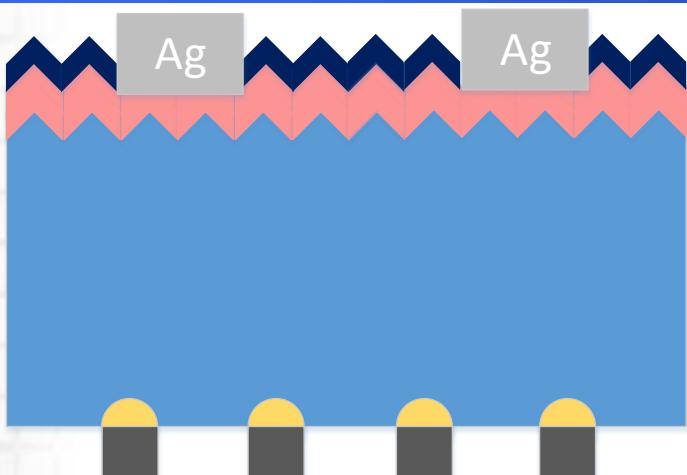


Fig. 3. Si 2p spectra of (a) GO coated Si/SiO<sub>2</sub> sample and (b) uncoated Si/SiO<sub>2</sub> sample showing a shift from the oxide peak on the coated sample and the shift and splitting of the Si 2p<sub>3/2,1/2</sub> peak.

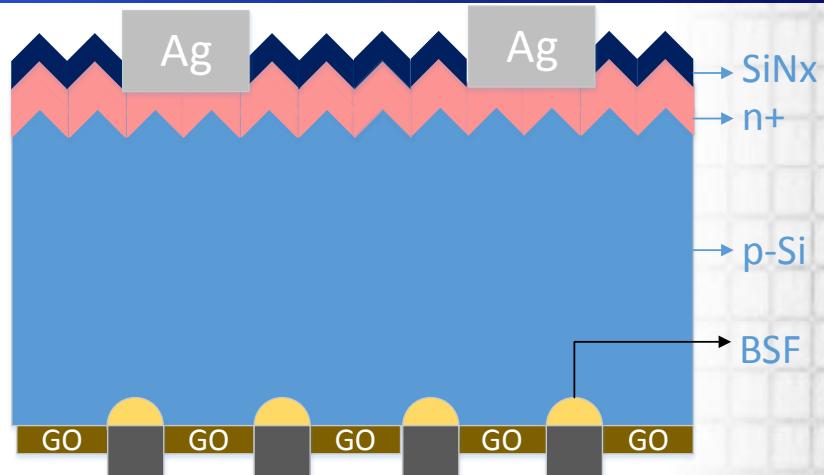
Ref: University of Manchester, SEMSC, 2018  
University of New South Wales, PVSC 2019

# Solar Cell w/o High T process

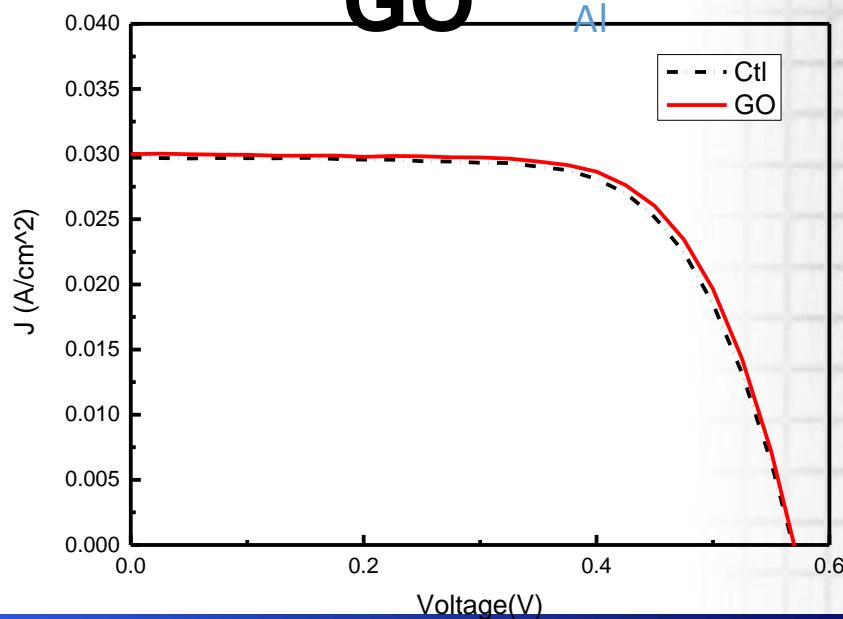
# Bifacial Structure



Ctl

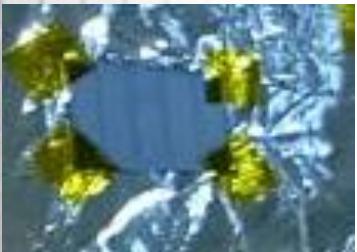


GO



	Voc(V)	Jsc(mA)	FF	η(%)
Ctl	0.568	29.73	0.73	11.47
GO	0.570	29.99	0.75	11.74

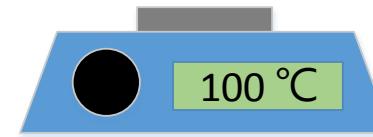
# Experimental Process II for Bifacial Structure



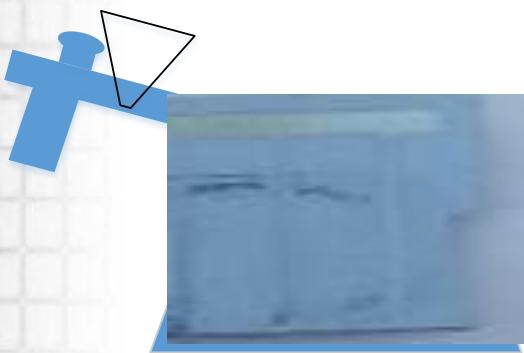
Taking something cover  
busbar



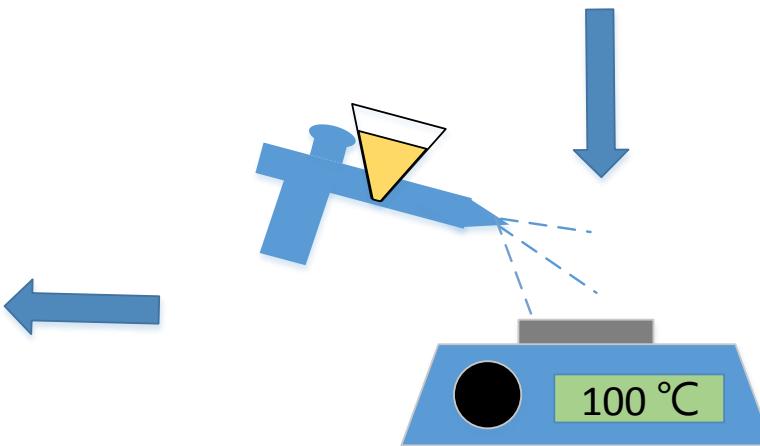
Drop GO into spray gun



Preheat to 100 degrees



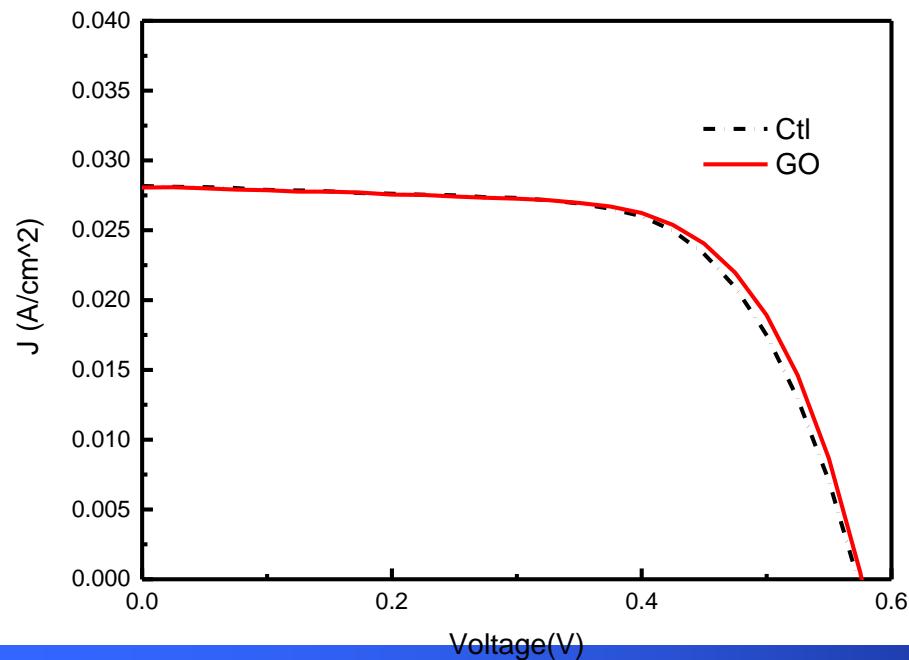
Spray until the liquid is  
exhausted



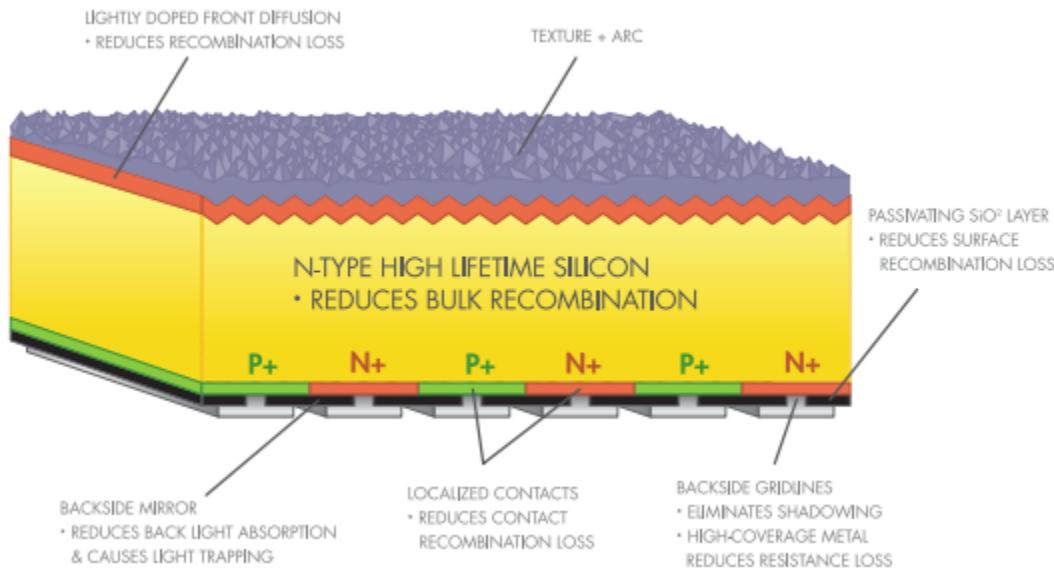
Use a spray gun in an appropriate way so that  
the sprayed liquid can evaporate immediately

# *Results from Bifacial Structure II*

	Voc(V)	Jsc(mA)	FF	η(%)
Ctl	0.573	28.17	0.72	10.61
GO	0.576	28.06	0.73	10.82



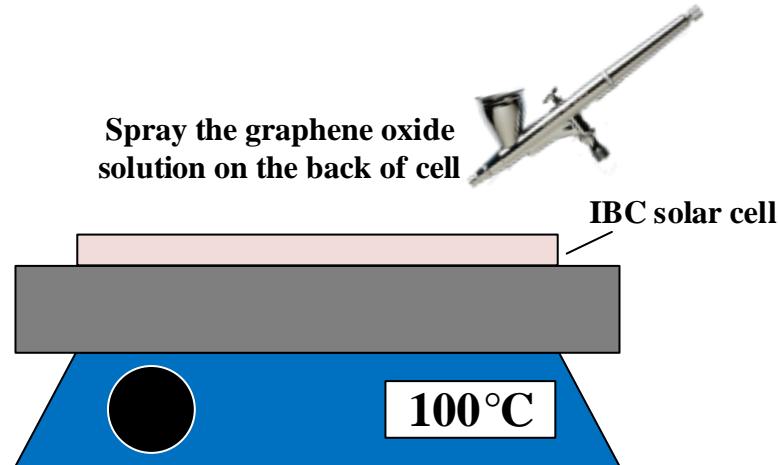
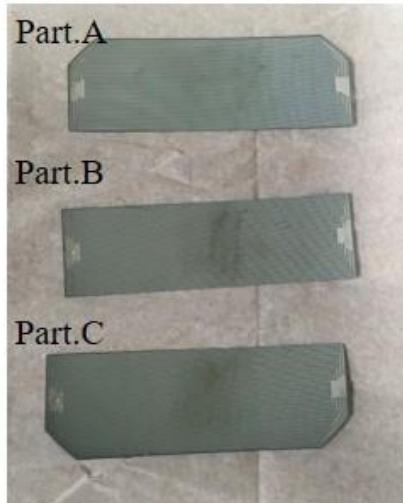
# *GO on Interdigitated back contact (IBC)*



**Back GO Passivation within electrodes**

Ref. <https://us.sunpower.com/sites/sunpower/files/media-library/brochures/sunpower-solar-panels-are-most-efficient-solar-panels-pv-industry.pdf>

# IBC電池上GO前後的電池表現

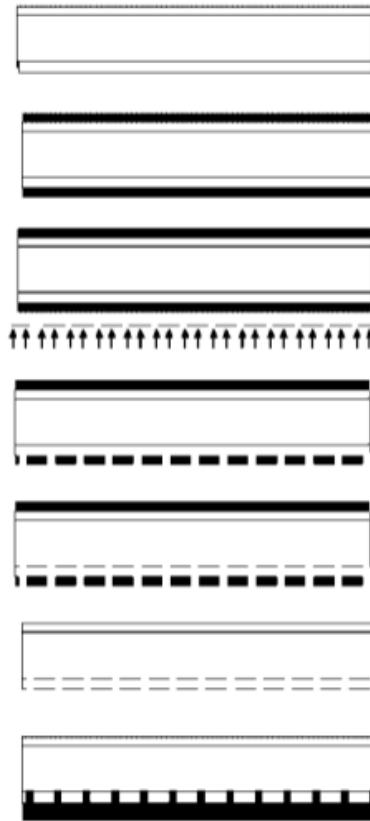


上GO 前	Illuminated area( $\text{cm}^2$ )	Voc(V)	Isc(mA)	FF	$\eta$ (%)
Part.A	28.6	0.625	0.857	0.72	13.42
Part.B	24.7	0.622	0.753	0.67	12.63
Part.C	28.6	0.631	0.870	0.74	14.17

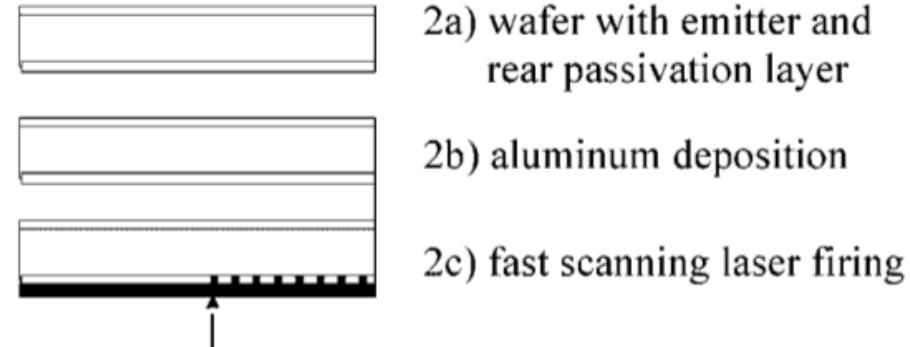
上GO 後	Illuminated area( $\text{cm}^2$ )	Voc(V)	Isc(mA)	FF	$\eta$ (%)
Part.A	28.6	0.631	0.904	0.72	14.28
Part.B	24.7	0.627	0.909	0.66	13.48
Part.C	28.6	0.635	0.909	0.77	15.62

# Laser-fired Contacts (LFC)局部加熱

1) photolithographic process



2) LFC process



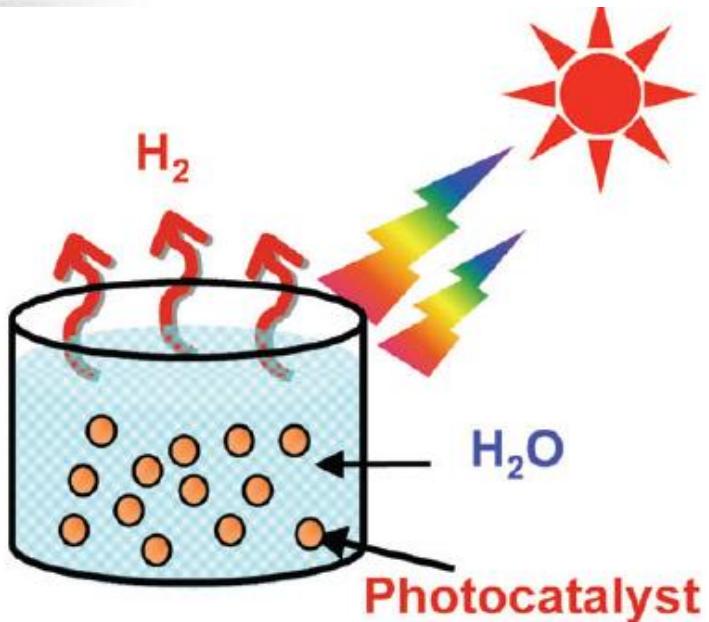
Ref. Prog. Photovolt: Res. Appl. 2002; 10:29

# Outline

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- Introduction
- Passivation Technologies
- GO for Solar Cell Passivation
- GO for Solar Water Splitting
- Summary

# 水分解產氫



(iii) Construction of surface reaction sites for  $\text{H}_2$  evolution

(ii) Charge separation and migration to surface reaction sites

(ii) Suppression of recombination

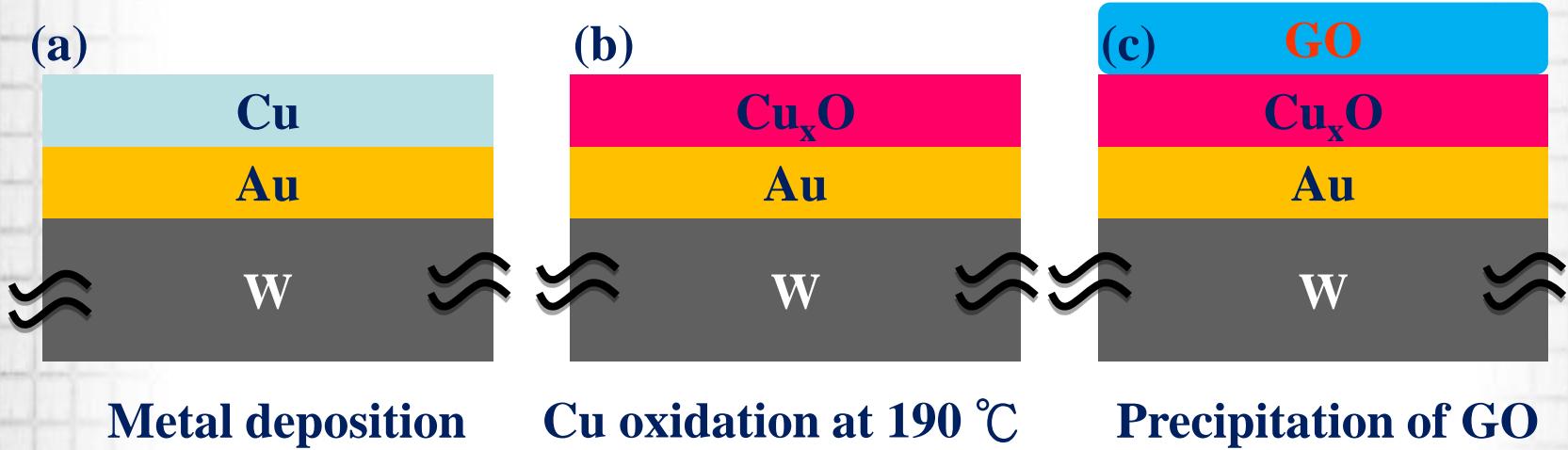
(i) Photon absorption  
→ Generation of  $e^-$  and  $h^+$  with sufficient potentials for water splitting (band engineering)

(iii) Construction of surface reaction sites for  $\text{O}_2$  evolution

- 在(半導體)光觸媒的幫忙下，可利用太陽能分解水產出  $\text{H}_2$  及  $\text{O}_2$  而不需要外加偏壓或犧牲試劑
- $\text{H}_2$  能用於燃料電池，其燃燒放能只排放出水( $\text{H}_2\text{O}$ )，為潔淨能源

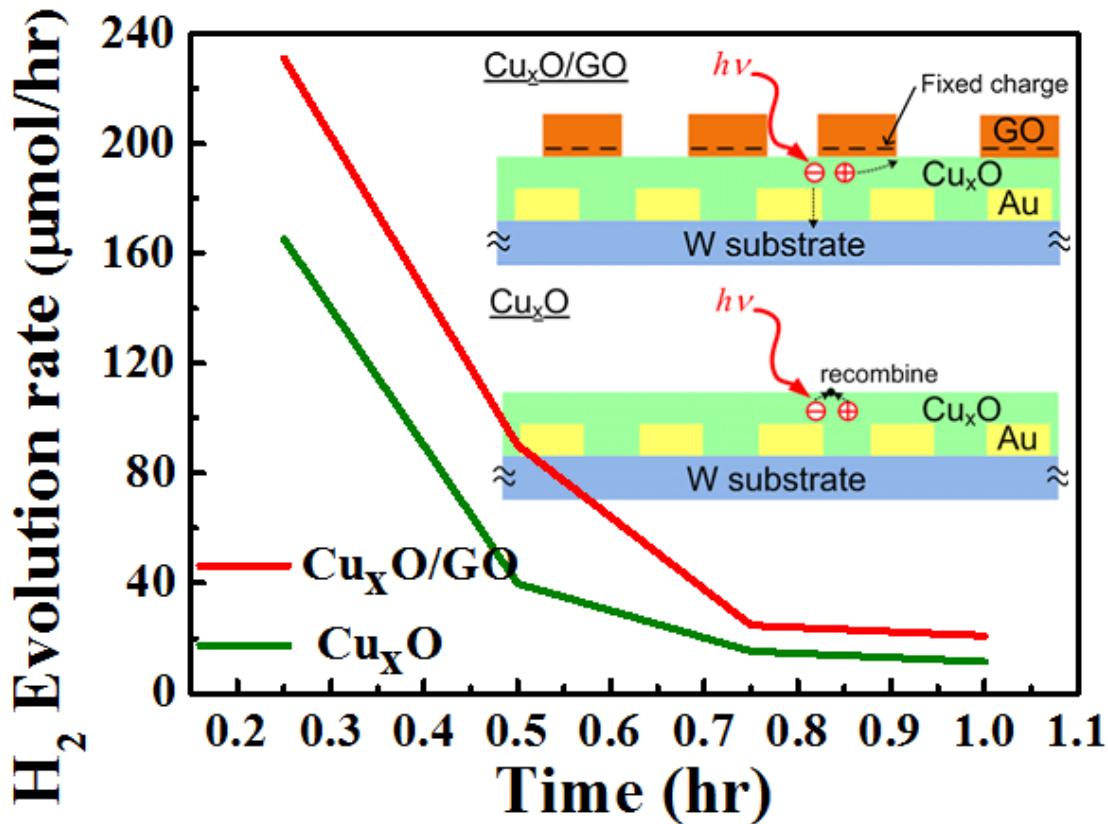
Ref. Chem. Soc. Rev., 2009, 38, 253–278

# Device Structure



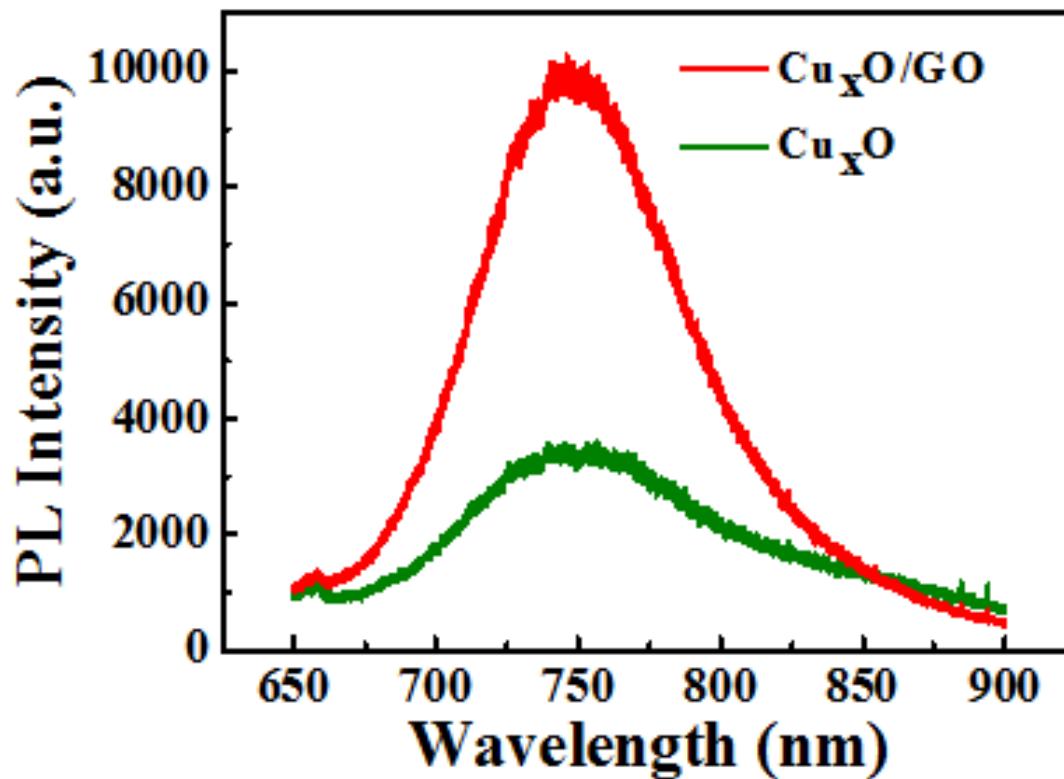
- W 提供良好導電率(相較於矽)
- Au and Cu: each 20 nm
- 在空氣中以190°C 加熱10 hr 以將Cu氧化

# 產氫速率



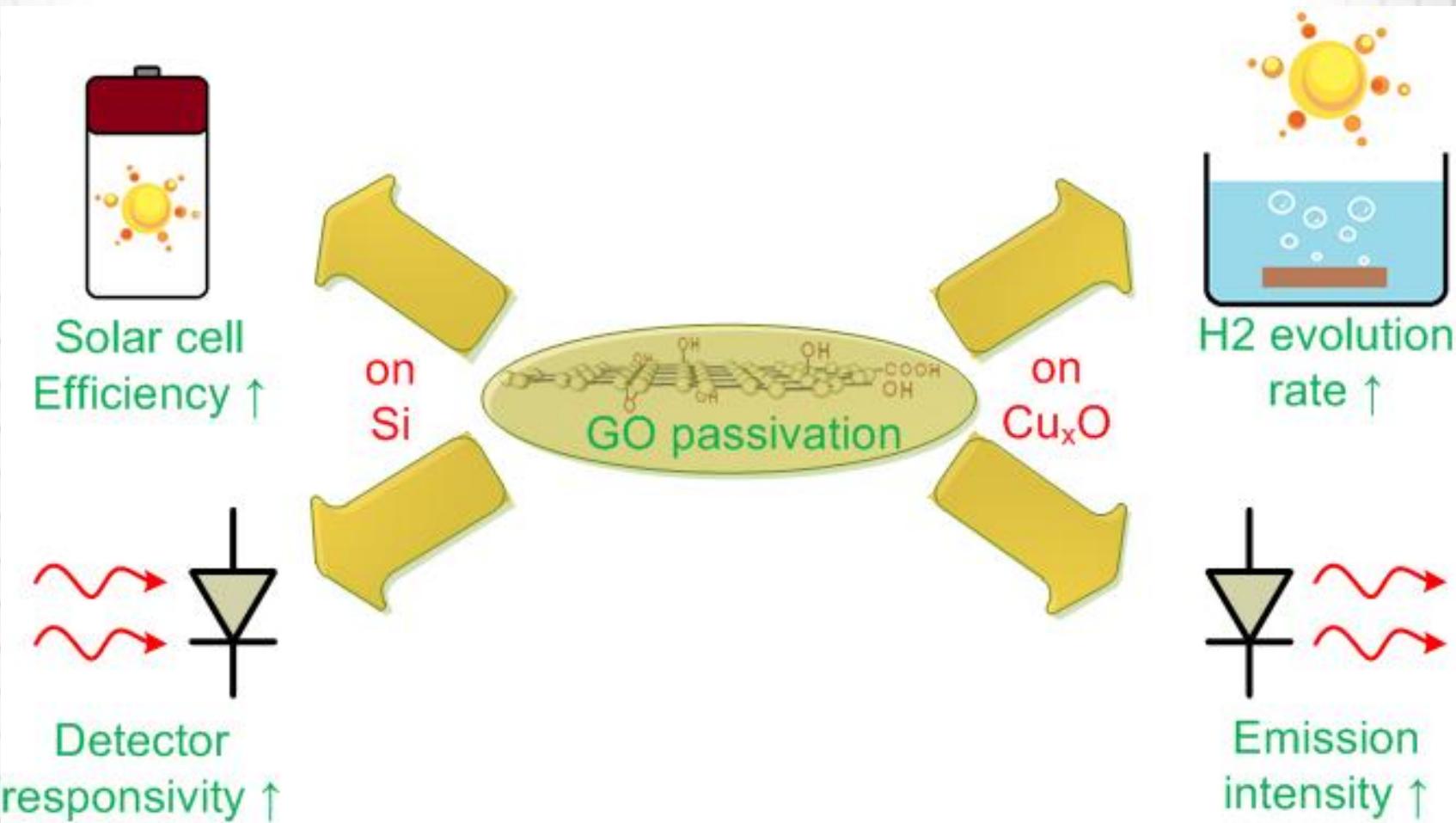
- $\text{Cu}_x\text{O}/\text{GO}$  及  $\text{Cu}_x\text{O}$  樣品一開始的產氫速率分別是  $230$  及  $170 \mu\text{mol}/\text{hr}$
- 多蓋一層  $\text{GO}$ ，產氫速率提升  $35\%$ ，原理如插圖，一樣是 passivation 貢獻

# GO增強PL 強度



- 以 632 nm (w/ energy <  $E_g$  of GO) 雷射照射樣品，觀測在  $\text{Cu}_x\text{O}$  中電子電洞對復合放出的光
- 一樣可藉由 GO 的鈍化，減少了電子電洞對在表面的熱復合(因而有更多機會改藉由放光復合)

# Summary



# *Summary*

- 砂電池發展多年，要將效率往上繼續提升，仰賴好的鈍化技術。無論是 $\text{PER}_x$ 背部的 $\text{Al}_2\text{O}_3$ 、HJT的a-Si、IBC正面 $\text{SiN}_x$ 與背面 $\text{SiO}_2$ 都是為鈍化而存在。
- 鈍化可以抑制光生電子電洞對的復合，提高載子的lifetime，進而提升太陽電池效率。
- 若能將氧化石墨烯(GO)用於無須高溫的製程，有機會利用其化學塗佈方式，降低鈍化的成本。

***Thank you for your attention!***